

Superconductivity in B doped Silicon and diamond

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Close collaboration with :

X.Blase : ***ab initio calculations*** - L.Ortega : **X-Rays**

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J. Boulmer, T. Kociniewski, and D. Débarre : **sample growth (GILD), X-rays**

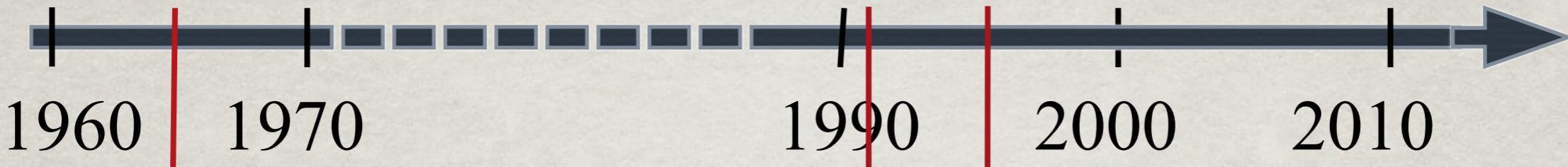
Institut d'Electronique Fondamentale,
CNRS, Université Paris Sud, Orsay, France

G. Prudon, C. Dubois : **Secondary Ion Mass Spectroscopy (SIMS)**

Institut des Nanotechnologies de Lyon,
CNRS and INSA, Villeurbanne, France

OUTLINE

- (short) historical revue on
superconducting group IV superconductors
[covalent superconductors]
a new route to high temperature superconductivity....
- **Diamond** : superconductivity vs metal-insulator transition
- **Superconducting silicon** thin films

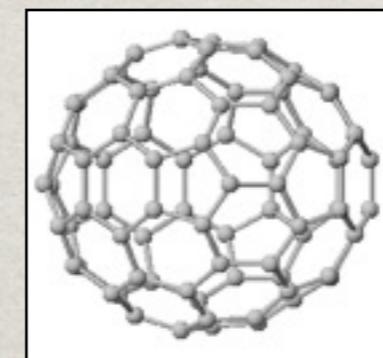


M.L.Cohen (1964)

J.F.Schooley et al. : SrTiO_3

R.A.Hein et al. : Ge_{1-x}Te

but T_c limited to a few 100mK



R.M.Fleming et al. (1991)

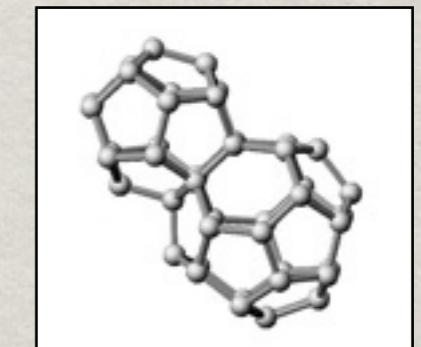
C60 buckyball, mostly **sp²** coordination (folded graphene), semiconducting molecular solid (face centered cubic structure)

Narrow (t_{1u}) empty **band** which can be filled by intercalation of alcali elements in the cavities between the balls

$T_c \sim 30\text{K}$ in Rb_3C_{60}

90' : Cage structures

H.Kawaji et al. (1995)



Silicon clathrates : 3D semi conductors made of face-sharing Si n -clusters ($n = 20, 24, 28$). As in standard Si, each atom is fourfold (**sp³**) coordinated

large doping can be obtained by **intercalation** in the center of the cages

$T_c \sim 4\text{K}$ in $\text{NaBa}_2\text{Si}_{46}$

[even 7K in $\text{Ba}_8\text{Si}_{46}$ D.Connetable et al. 2003]

$$\text{electron-phonon coupling constant} \quad \lambda_{e-ph} = N \times V_{e-ph}$$

Fullerenes

$N \sim 10$ states/eV/spin/cell
 $V_{e-ph} \sim 70$ meV
($\lambda_{e-ph} \sim 0.7$)

Si-clathrates

$N \sim 40$ states/eV/spin/cell
 $V_{e-ph} \sim 20$ meV
($\lambda_{e-ph} \sim 0.8$)

V_{e-ph} can be *theoretically* increased by

reducing the size of the ball
(i.e. increasing the **sp3 character**)

replacing Si by **C**

$V_{e-ph} \sim 210$ meV in C_{28}

(N.Breda et al. 2000)

$V_{e-ph} \sim 150-250$ meV

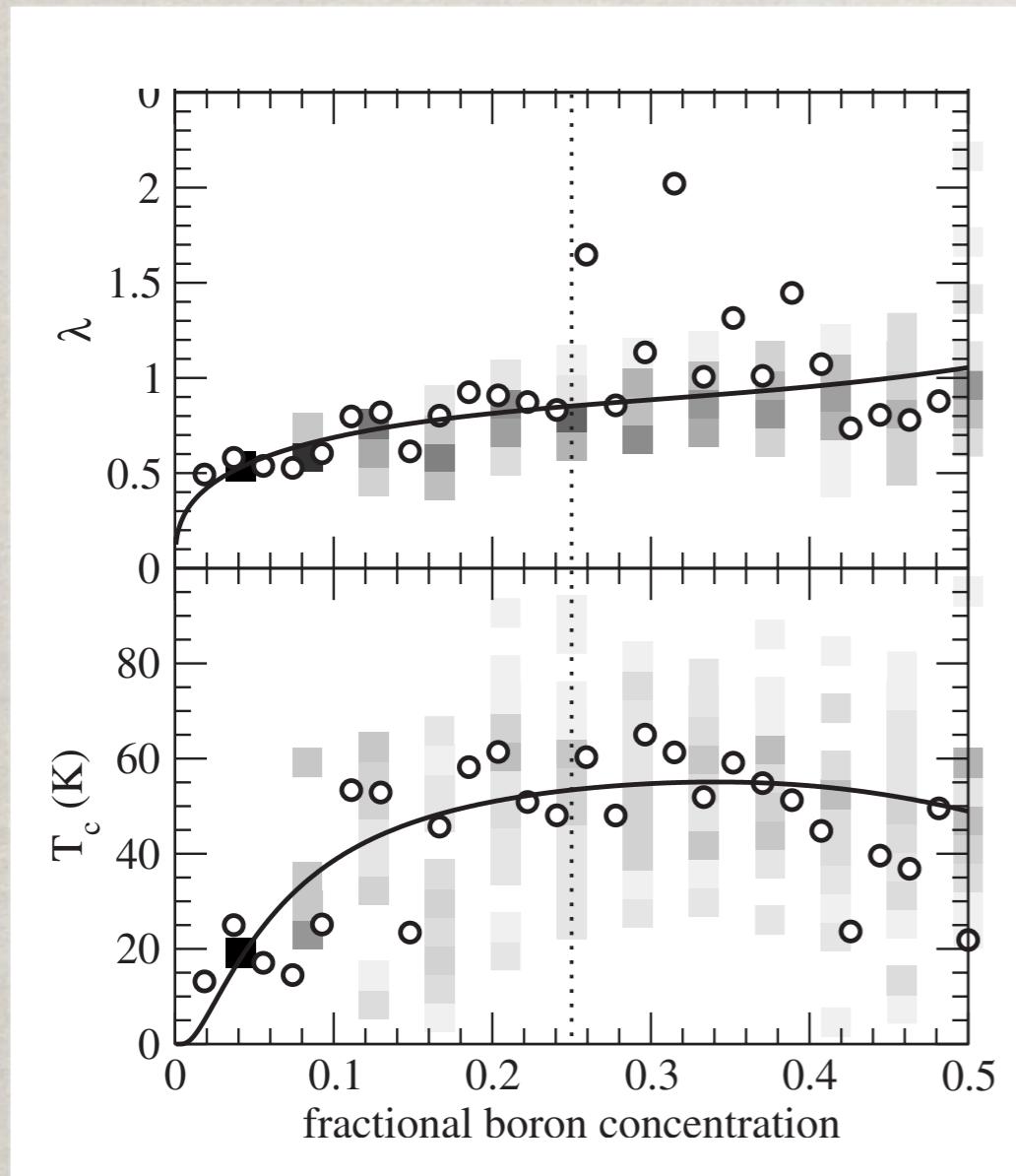
(D.Connable et al. 2003)

expected T_c above 200K !!!

B doped **Diamond** : BC_{53} (X.Blase et al. 2003)

$V_{e-ph} \sim 280$ meV ...

... and N depending on the Boron concentration



Moussa et al. 2008
(see also Calandra et al. 2008)

T_c could reach ~ 60 K around ~ 30 at-%

Note : interesting Li_{1-x}BC system : semiconducting for $x=0$, *should* become superconducting for $x>0.2$ with $T_c \sim 150$ K for $x \sim 0.5$ (Rosner et al. 2002)



1960 1970

1990

2000

2010

MgB₂

Nagamatsu et al. 2001

B-hexagonal structure (similar to graphite)
but σ (sp²) band shifted to E_F
due to presence of Mg²⁺

$T_c \sim 39K$

B doped diamond

Ekimov et al. 2004

superconductivity (in sp³ band)
appears at the onset of
Metal Insulator Transition

T_c up to 10K ($n_B < 5\%*$)

CaC₆, YbC₆

Weller et al. 2005

Intercalated graphite
intercalant (~ free electron) ζ -band

$T_c \sim 11K$

Si:B

Bustarret et al. 2007

$T_c < 1K$

* for large doping :
- clustering of borons into inactive dimers
- increase of the interstitial boron content

and also B:SiC (Renet al.2007) or Ga:Ge (Herrmannsdorfer et al. 2009)

Superhardness : the B:C:N triangle

C (80-130 GPa)

B₄C (30 GPa), BN (62 GPa), BC₂N (76 GPa)

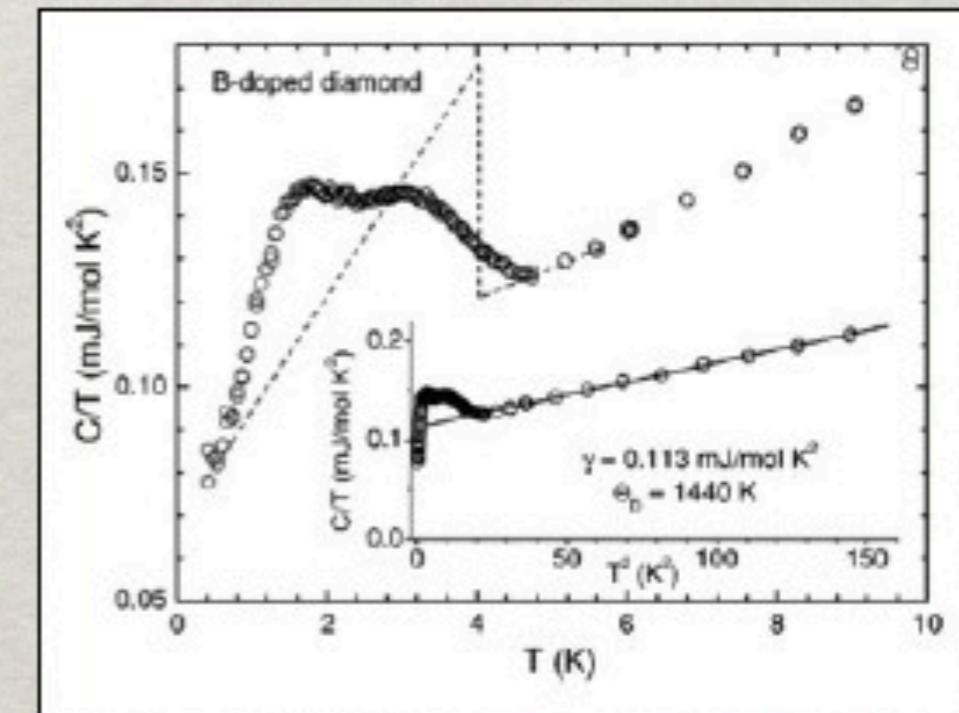
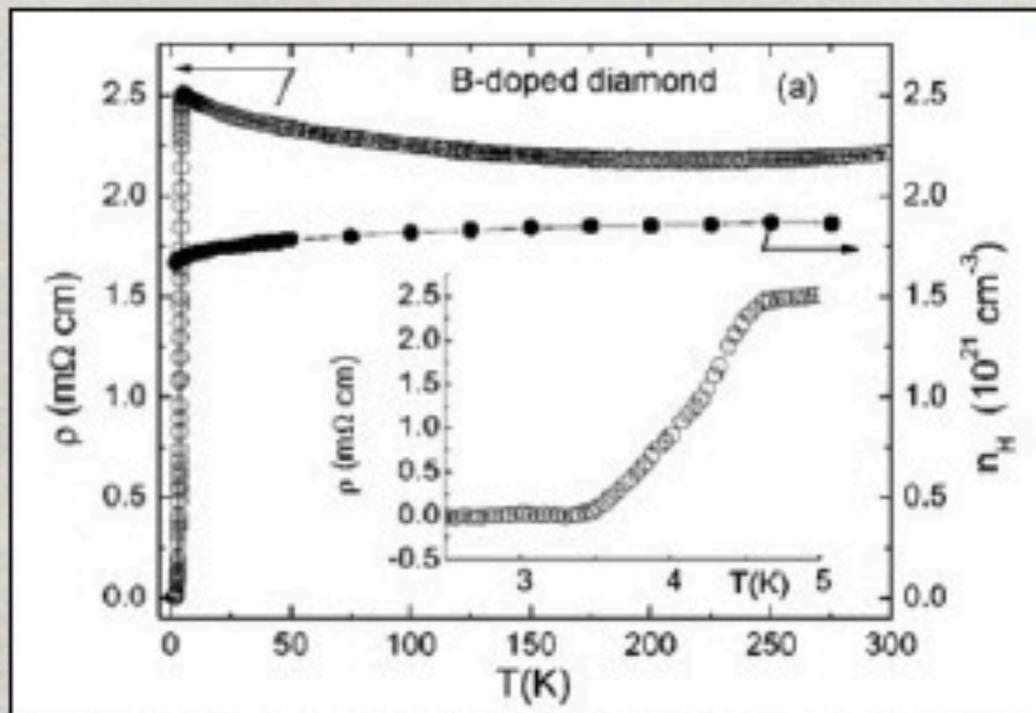
HPHT : 2500-2800 K, 8-9 GPa, 5 s

Graphite + B₄C \longrightarrow B-doped diamond + B₄C traces (Ekimov et al. 2004)

Doping level : 2-3 at % i.e. 3-5 10^{21} B/cm³

$T_c \sim 3K$

Specific heat measurements confirmed bulk superconductivity
(not filamentary) [Sidorov et al. 2005]



rapidly confirmed in [thick] epitaxial films (grown by plasma assisted CVD)

001-oriented type Ib diamond substrates

Hydrogen plasma + Methane (4%)

-> 0.5 μm -thick **buffer layer** of nonintentionally doped material

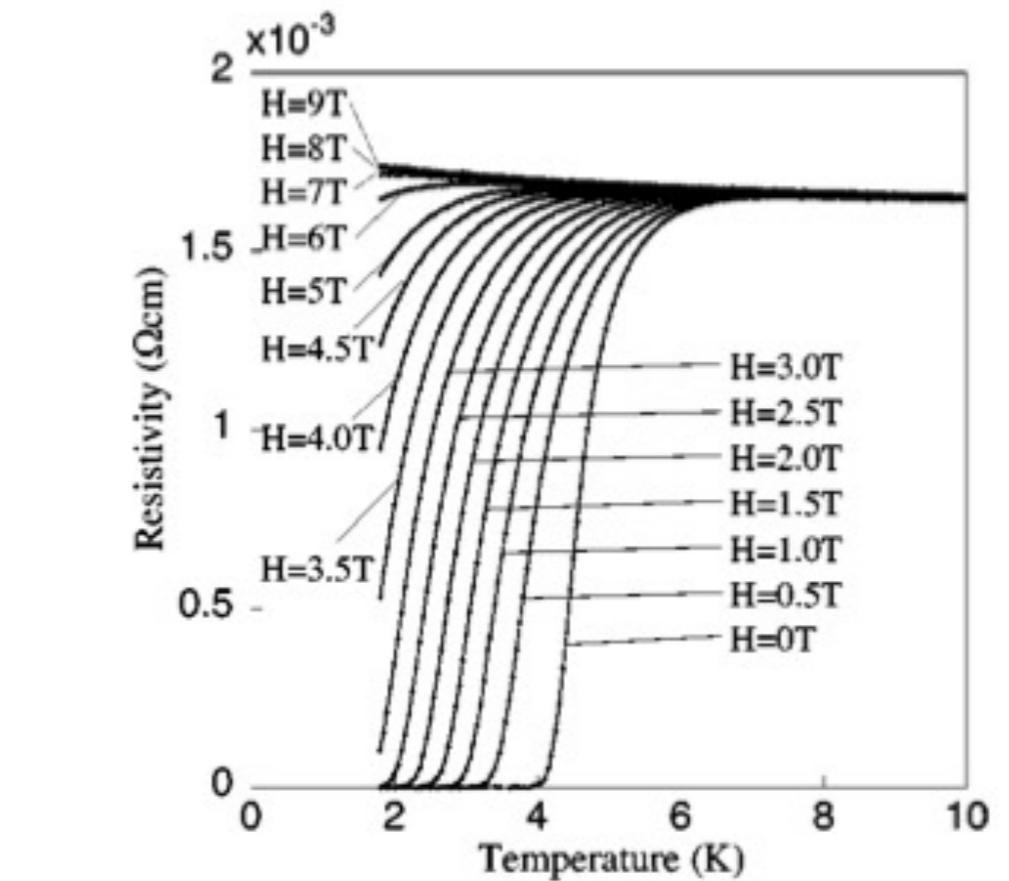
Diborane introduced in vertical silica wall reactor with [B]/[C] from 1500 to 3000 ppm

High quality **μm -thick p-type diamond epilayers**

x-ray diffraction : (shifted) narrow lines

FWHM \sim 10 arc sec ([004] peak) \sim substrate

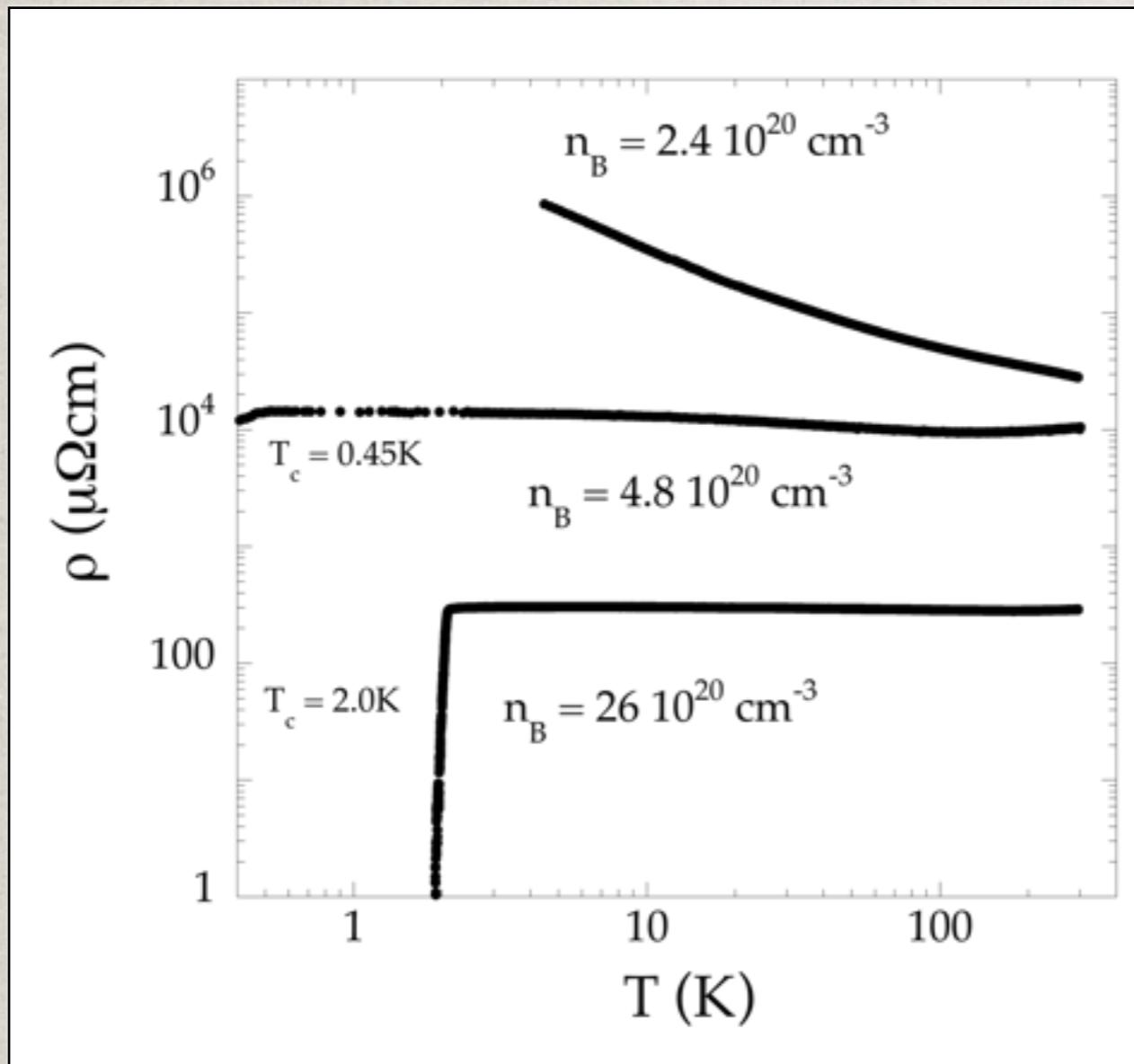
but n_B (still) < 2.5 at-%



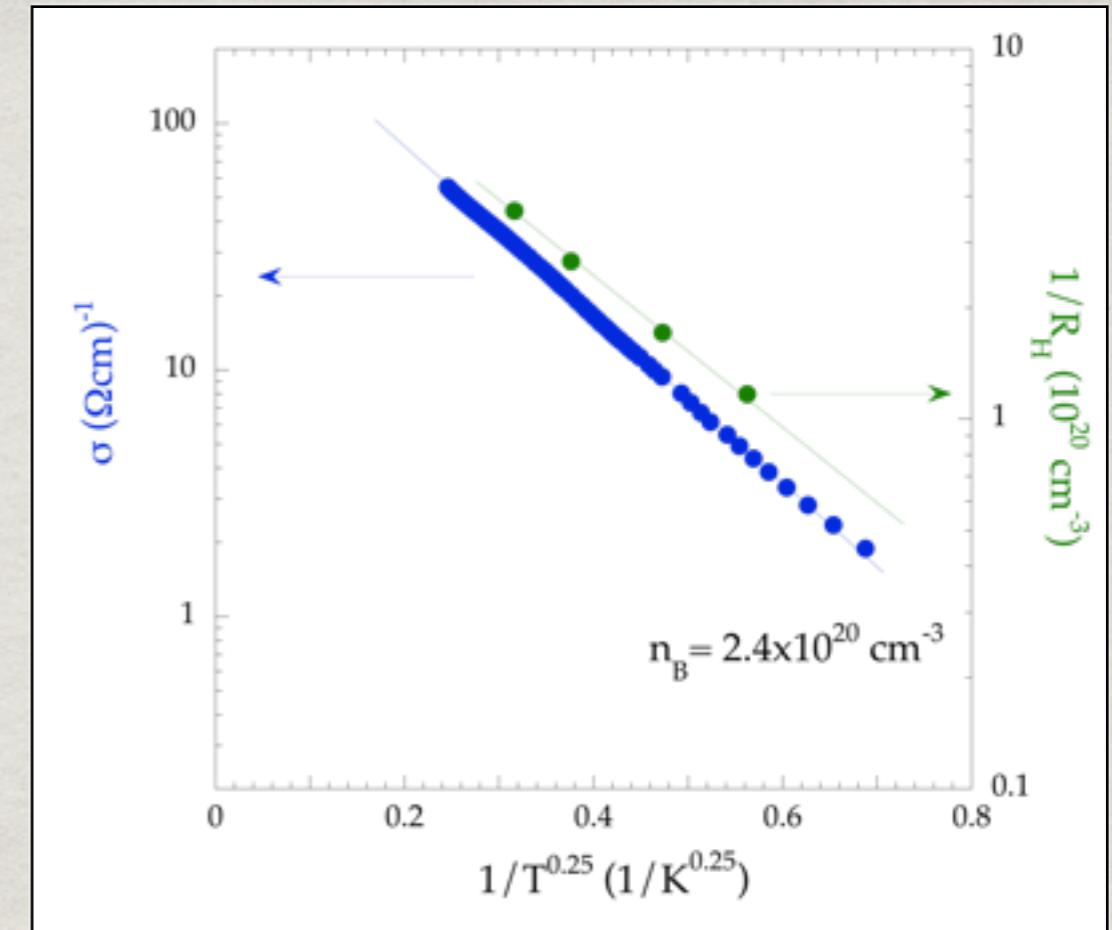
Y.Takano (2004)

[111] oriented
 $H_{c2}(0) \sim 10\text{T}$

T_c up to $\sim 10\text{K}$ for $10^{22}\text{cm}^{-3} = 5$ at-%



$n < n_c \sim 4.5 \cdot 10^{21} \text{ cm}^{-3}$
 Variable Range Hopping conductivity



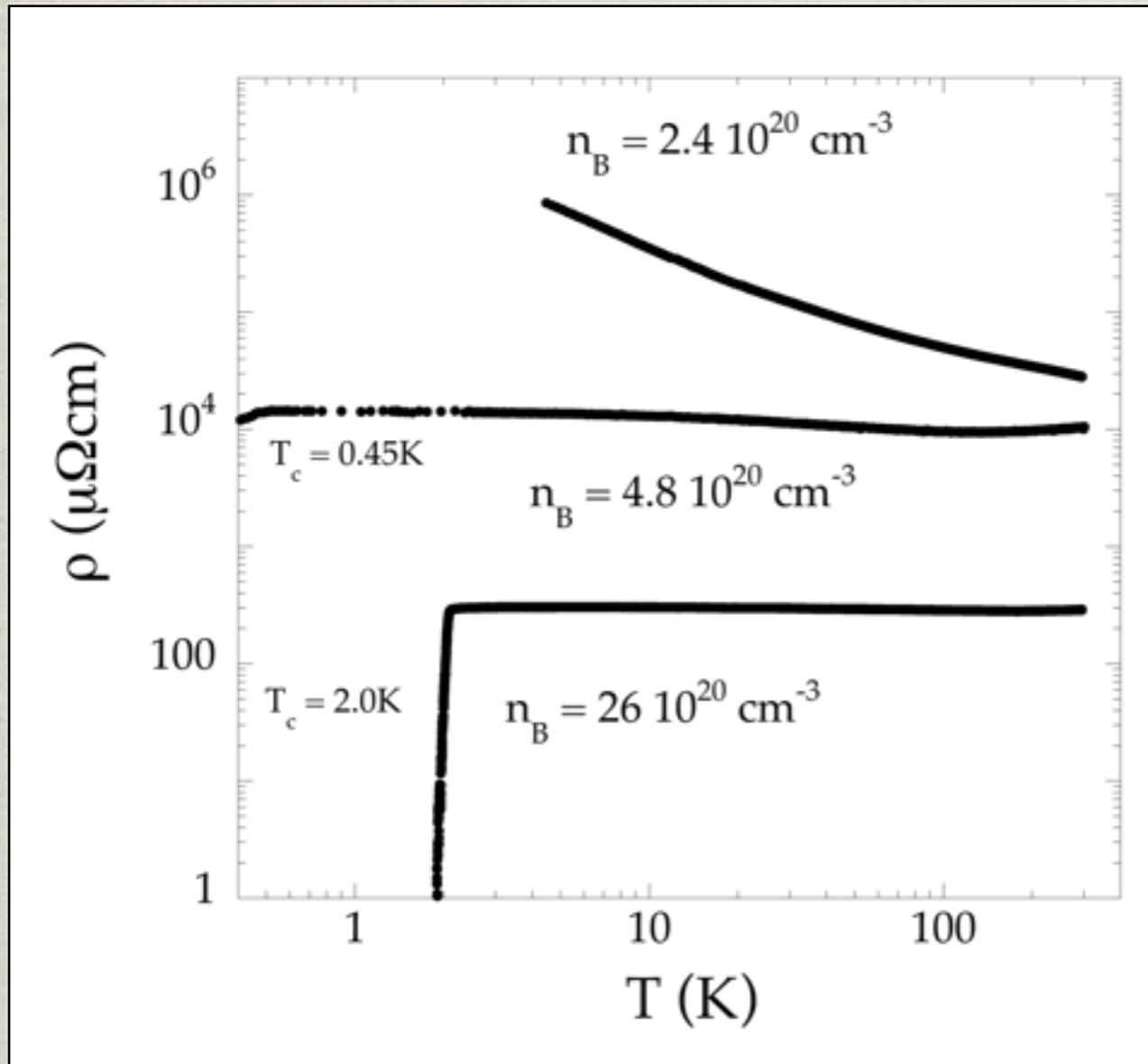
$$\sigma = \sigma_0 \exp[-(T_0/T)^{1/4}]$$

$$R_H = R_{H,0} \exp[-(T_{0,H}/T)^{1/4}]$$

$$\text{with } [T_{0,H}/T_0]_{\text{th}} = 0.15$$

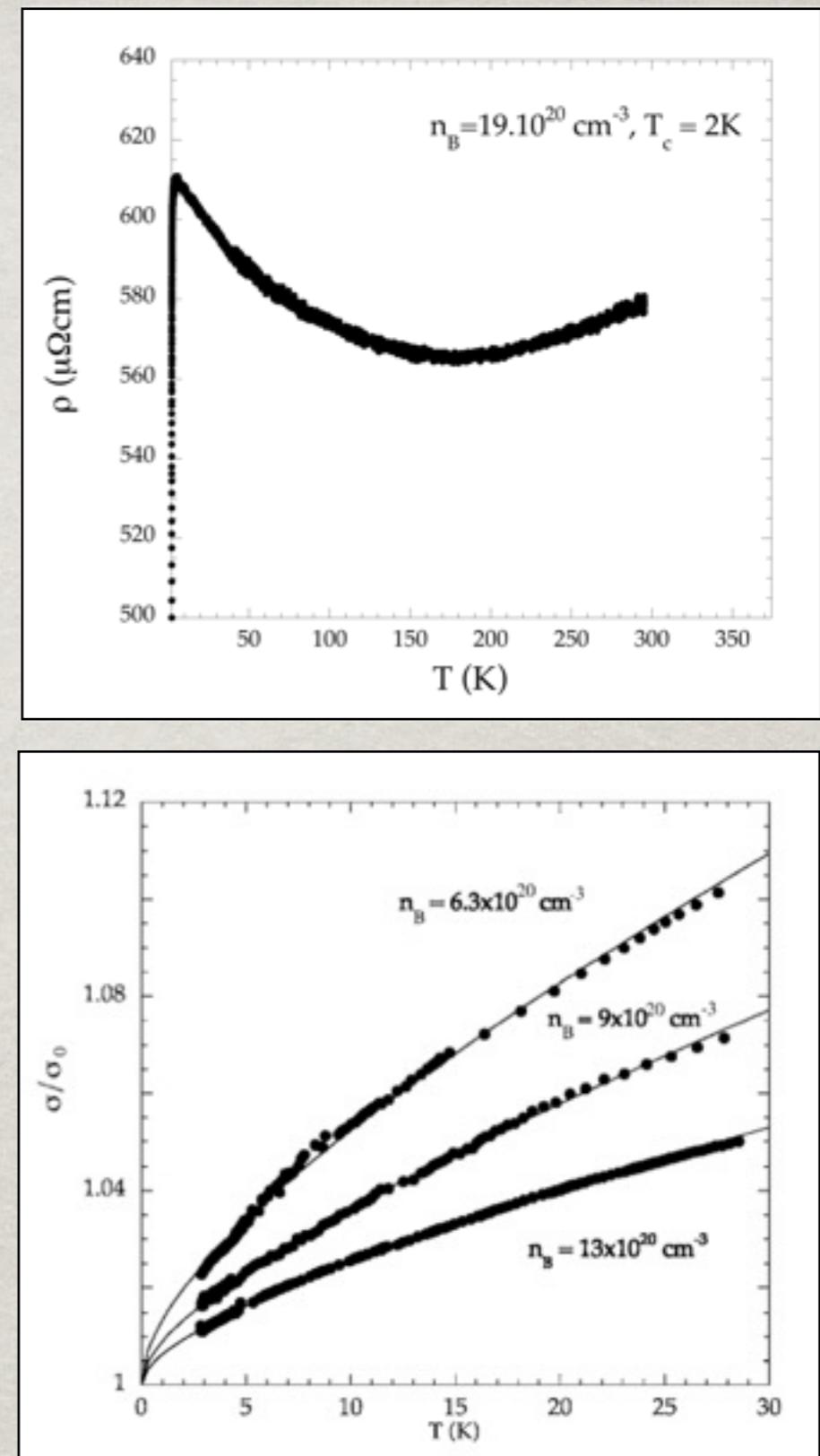
and $[T_{0,H}/T_0]_{\text{exp}} = 500/3700 \sim 0.13$
 $(n_B = 2.4 \cdot 10^{21} \text{ cm}^{-3})$

Quantum Interference effects (weak localisation +e-e interactions)

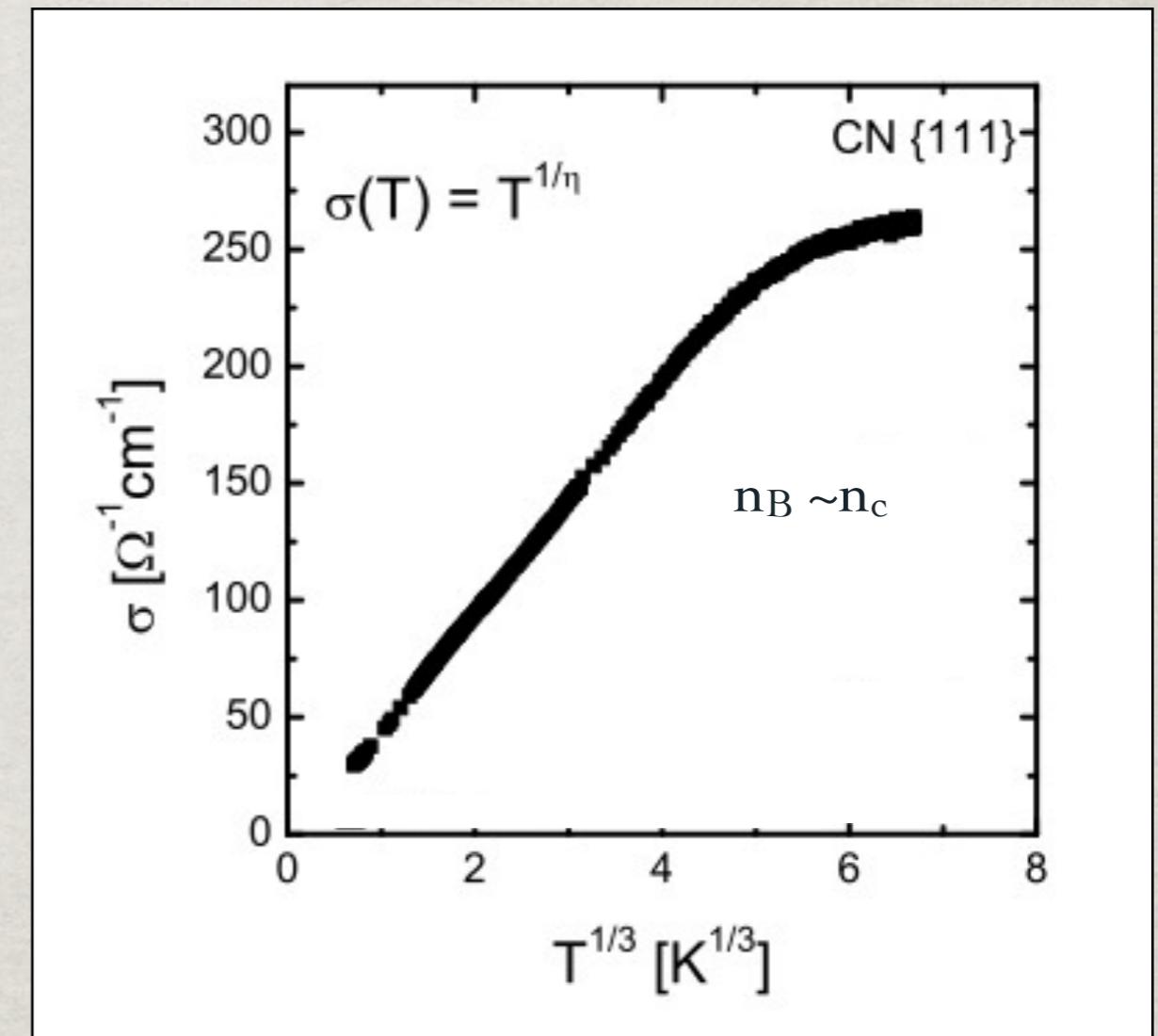
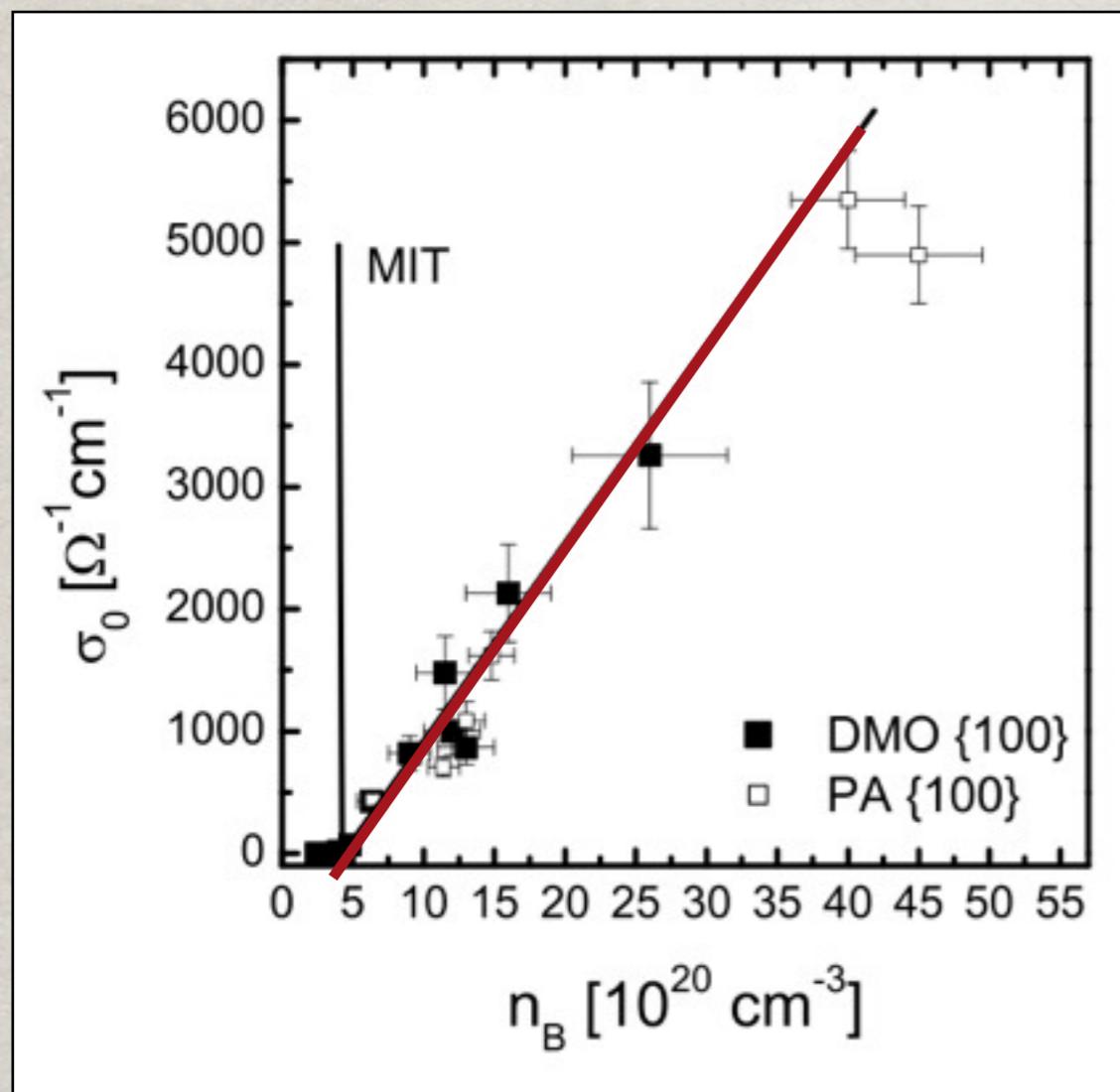


$$n > n_c \sim 4.5 \cdot 10^{21} \text{ cm}^{-3} (\sim 0.25 \text{ at-\%})$$

metal with E_F lying in the valence band
of the diamond
(Yokoya et al. 2005)



$$\sigma = \sigma_0 + AT^{1/2} + BT$$



$$\sigma_0 = 0.1(e^2/\hbar)(1/\xi)$$

$$a^*/\xi = (n_B/n_c - 1)^\nu$$

where a^* is the Bohr radius $\sim 3.5\text{\AA}$

$$\nu = 1$$

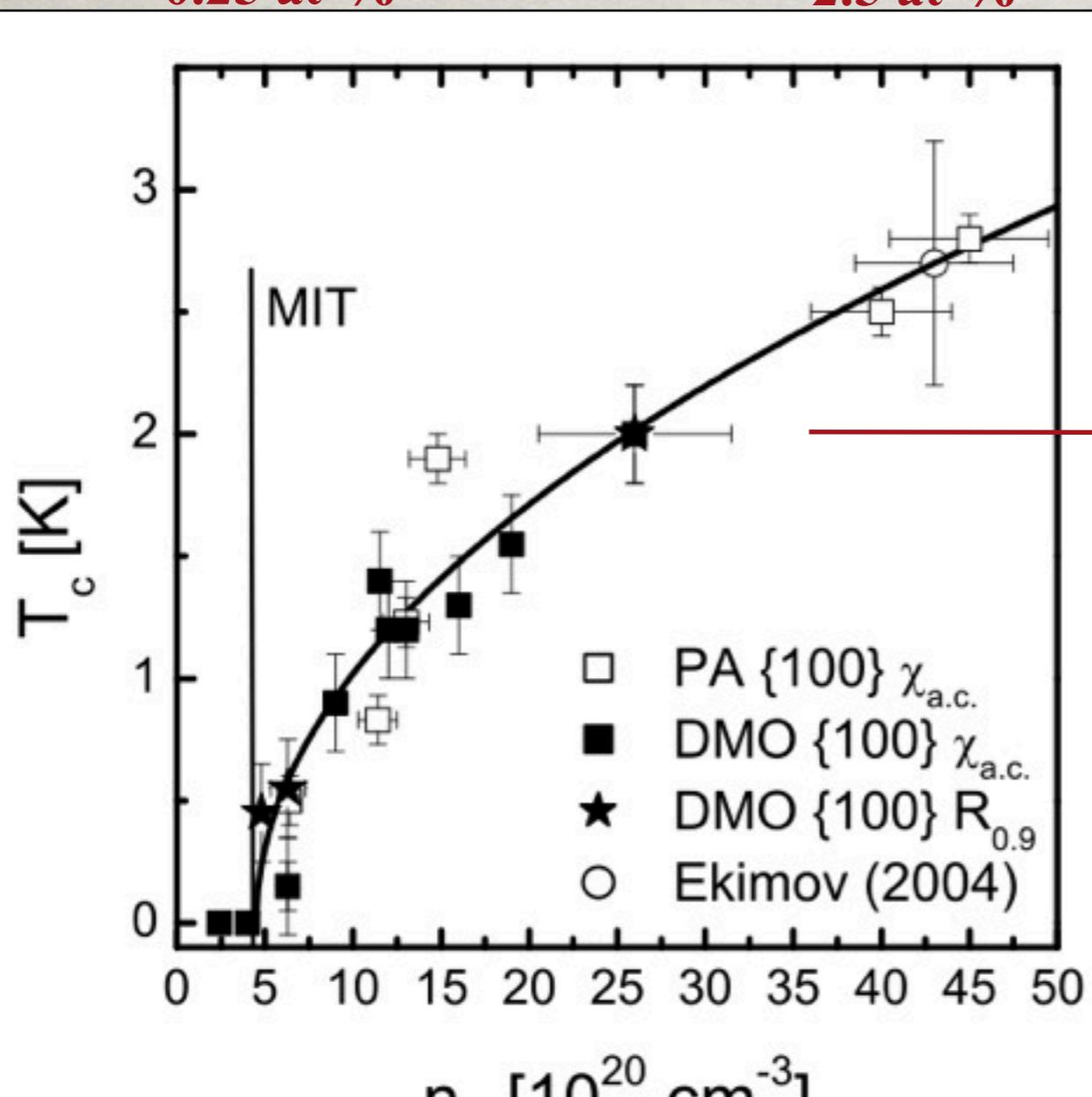
$$E \propto 1/\xi^\eta$$

for $n_B = n_c$

$$\sigma \propto T^{1/\eta}$$

$$\eta \sim 3$$

0.25 at-% \longrightarrow 2.5 at-%

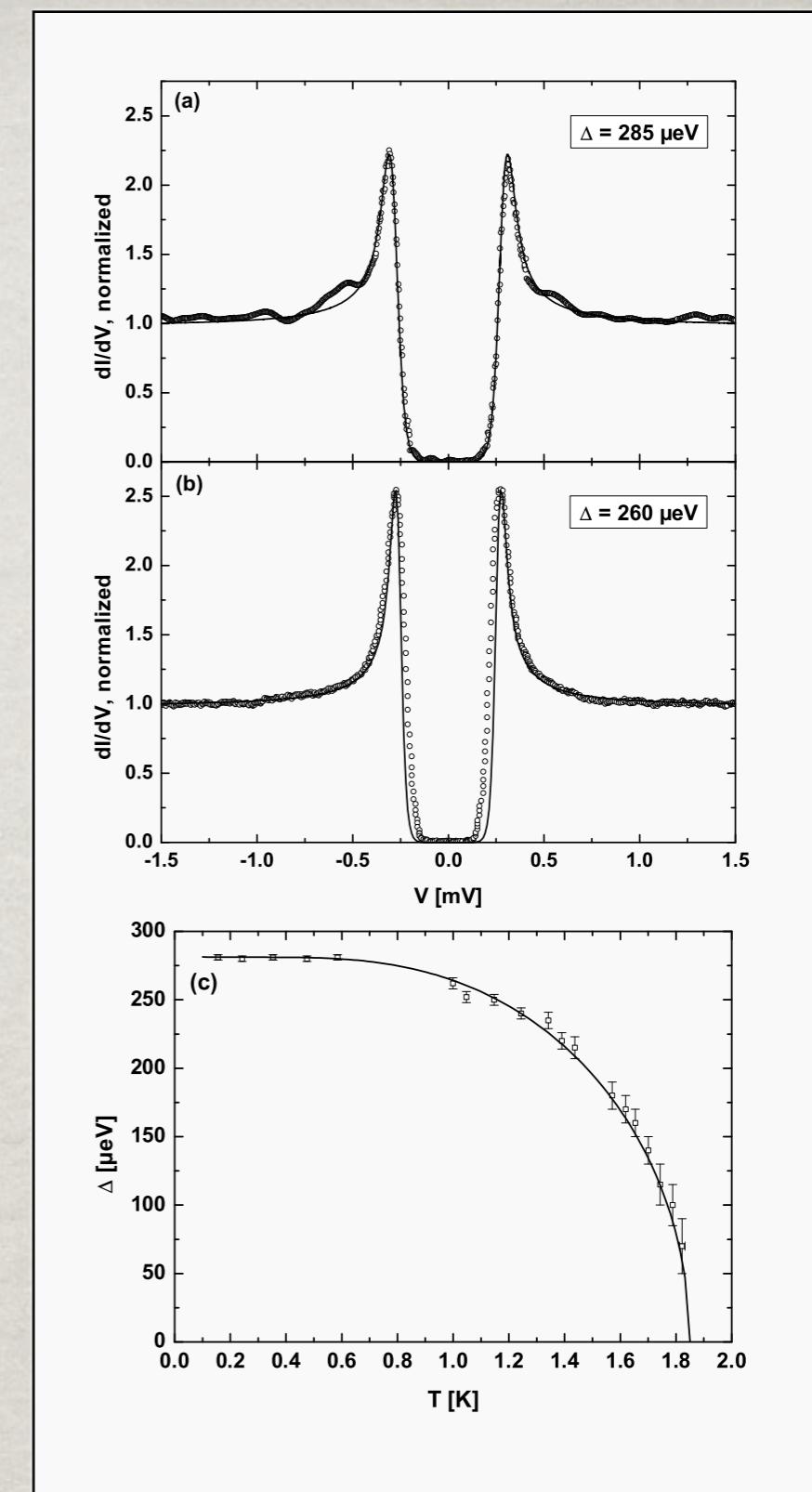


T.Klein et al. (2007) - P.Achatz (2008)

T_c remains *surprisingly high* close to n_c

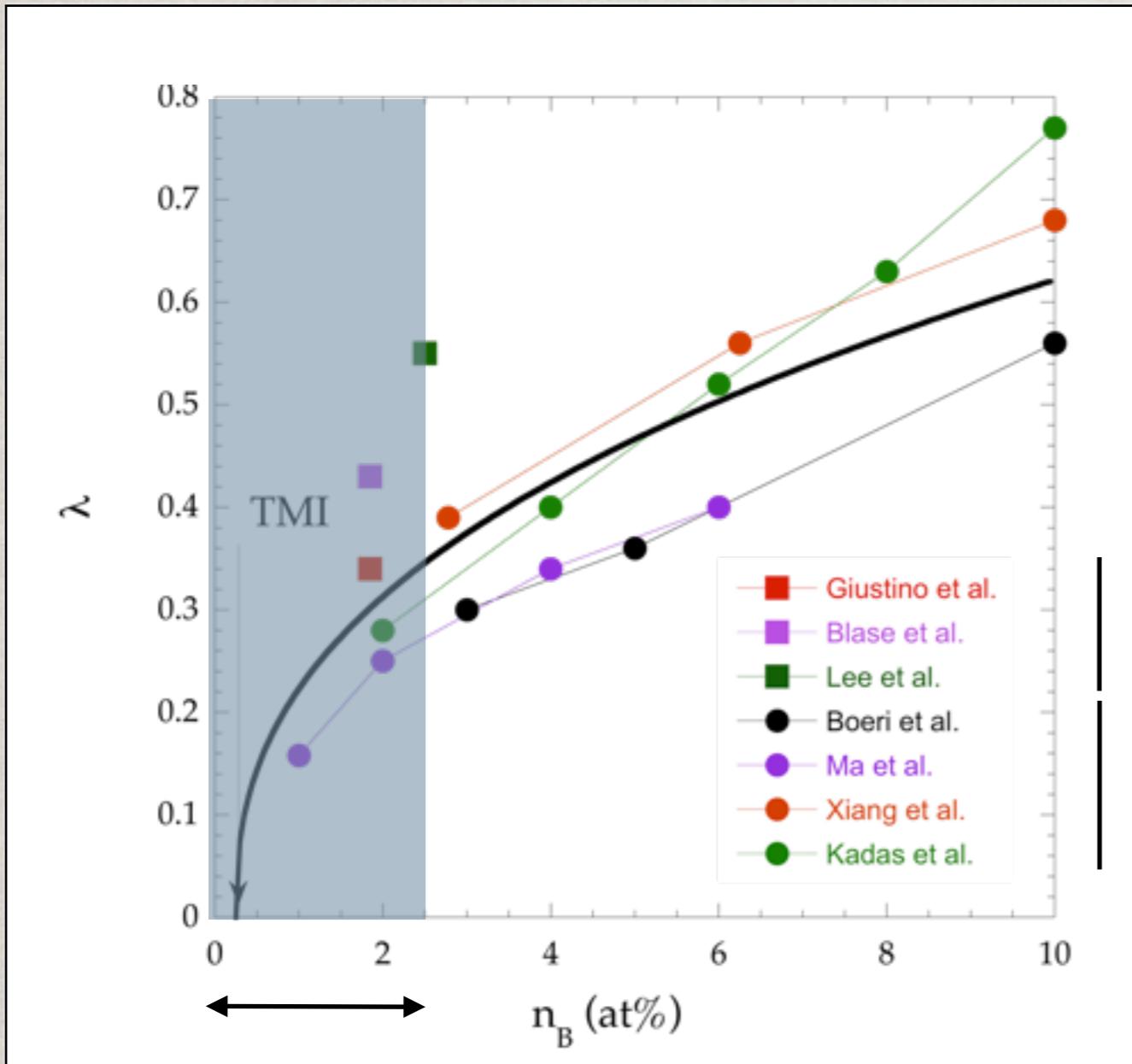
$$T_c \propto (n_B/n_c - 1)^\beta$$

$$\beta \sim 0.5 - 0.6$$



B.Sacépé et al. (2006)

Fully open gap with $\Delta/kT_c \sim 1.7$ i.e. close to BCS value



experimental range
for T_c measurements
poor overlap between
doping ranges

ab initio calculations $\rightarrow \lambda$

supercell method

virtual cristal approximation

$$T_c = \omega \exp \left[- \frac{1 + \lambda}{\lambda - \mu^*(1 + \lambda)} \right]$$

but *unknown* μ^* coefficient
(retarded Coulomb pseudopotential) $\mu^* = \frac{\mu}{1 + \mu \ln(\omega_{el}/\omega_{ph})}$

standard **metals**

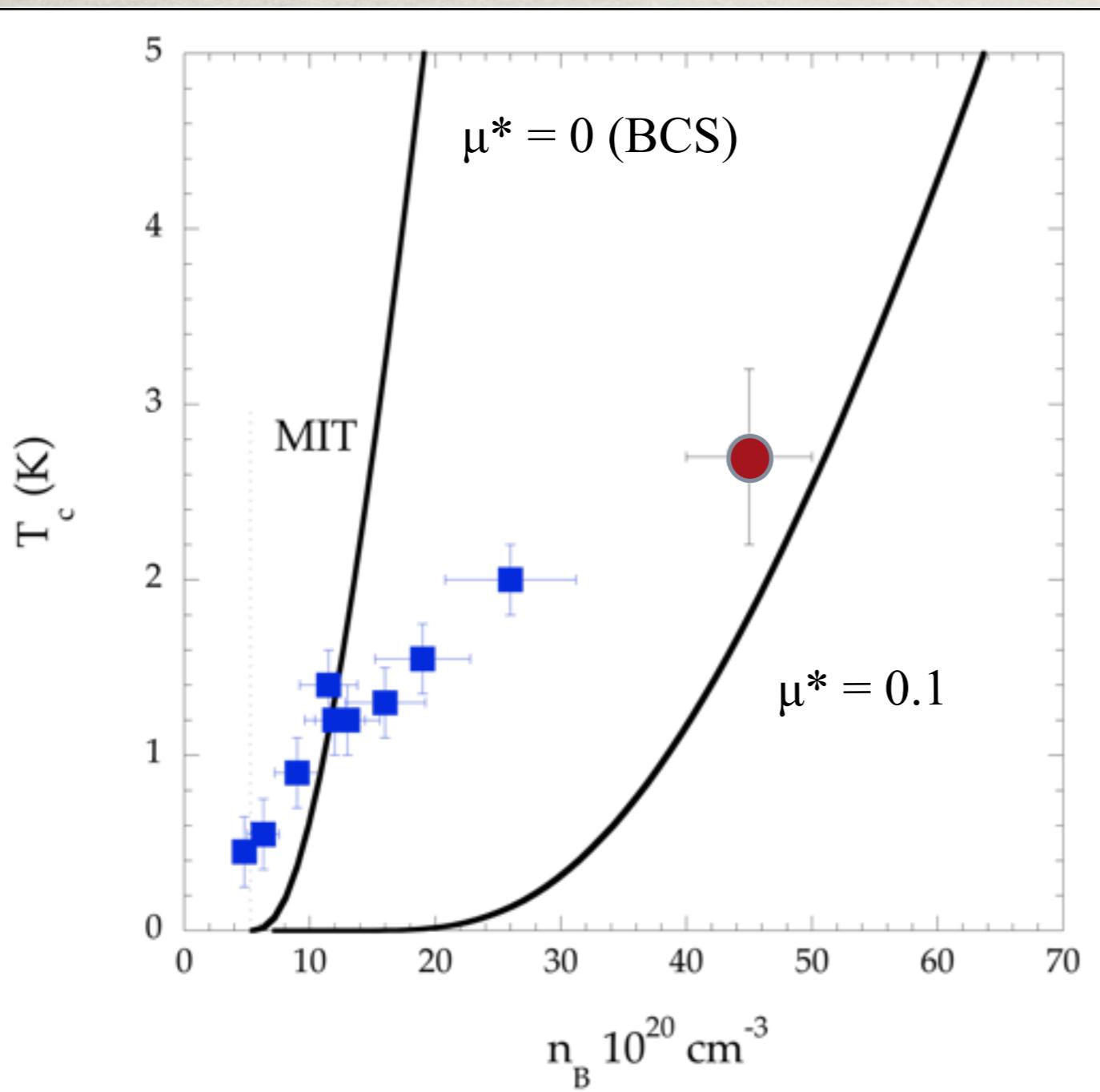
$\omega_{el}/\omega_{ph} \sim E_F/k_B\theta_D \sim 100$ leading to $\mu^* \sim 0.15$ ($< \mu$)

diamond

$\omega_{el}/\omega_{ph} \sim E_F/k_B\theta_D < 3$

inefficient retardation effects $\mu^* \sim \mu$
(similar effect in fullerenes for which $\mu^* \sim 0.3$ remains close to $\mu \sim 0.4$)

and μ is expected to tends towards 0 at the MIT ?



very reasonable agreement
between calculations and
 T_c obtained by Ekimov et al. (2004)
still taking $\mu^* \sim 0.1$

but for lower n_B values T_c much larger
than calculated values

can be associated with reduced μ (i.e. μ^*)
values in the vicinity of MIT

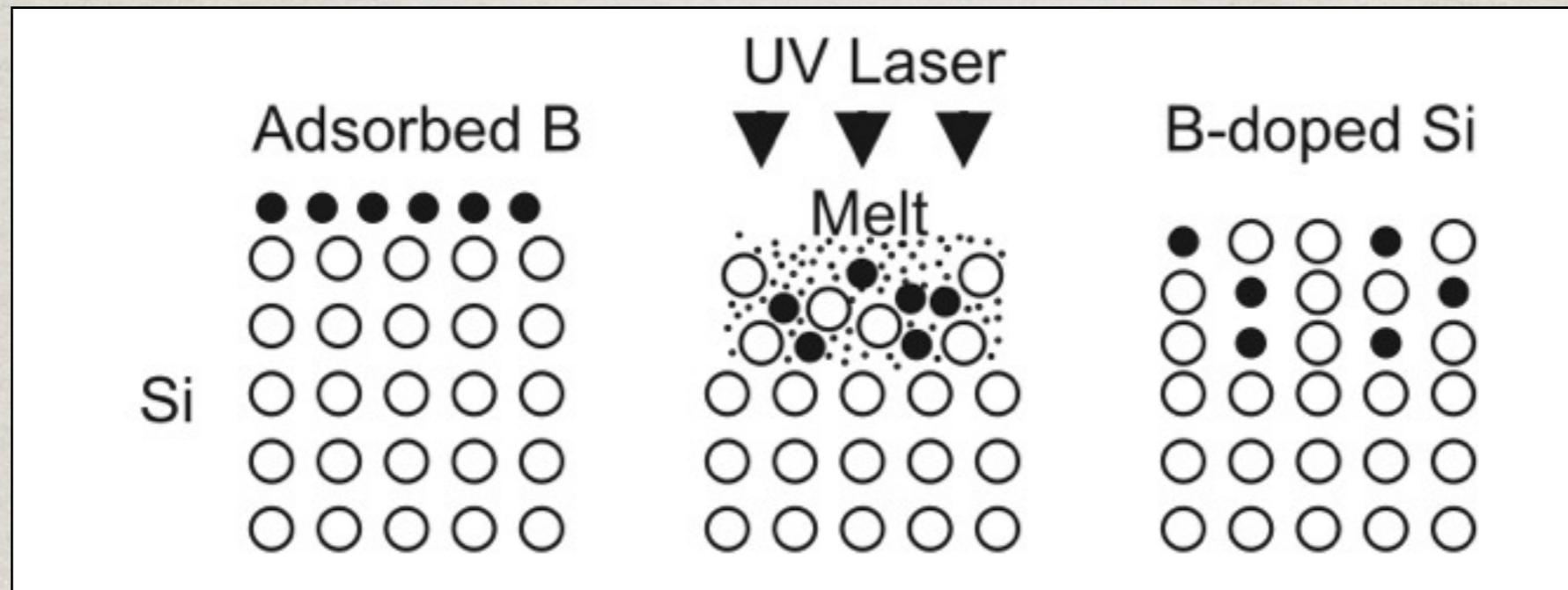
what about **SILICON**

$n_c \sim 10^{18} \text{ cm}^{-3}$

but **no superconductivity**
observed up to
 $n_B \sim 5 \times 10^{20} \text{ cm}^{-3}$
= SOLUBILITY LIMIT

-> Gas Immersion Laser Doping [IEF, Paris]

OUT OF EQUILIBRIUM TECHNIQUE



Recrystallization rate $\sim 10^{10}$ K/s

n_B increases with number of laser pulses

thickness of doped top layer increases with pulse duration (and laser energy)

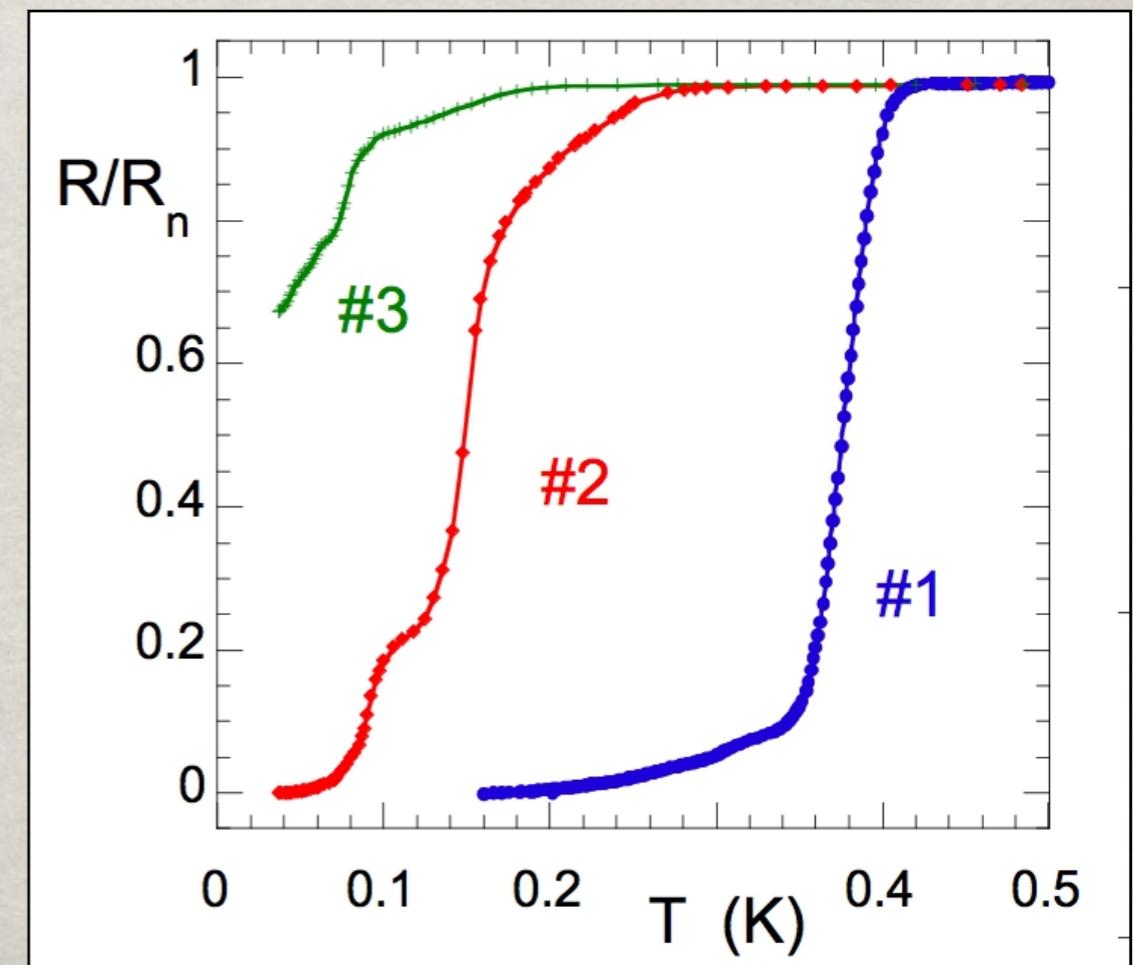
50ns (900mJ/cm²) <=> 100nm

170 nm-thick 4-5 at%

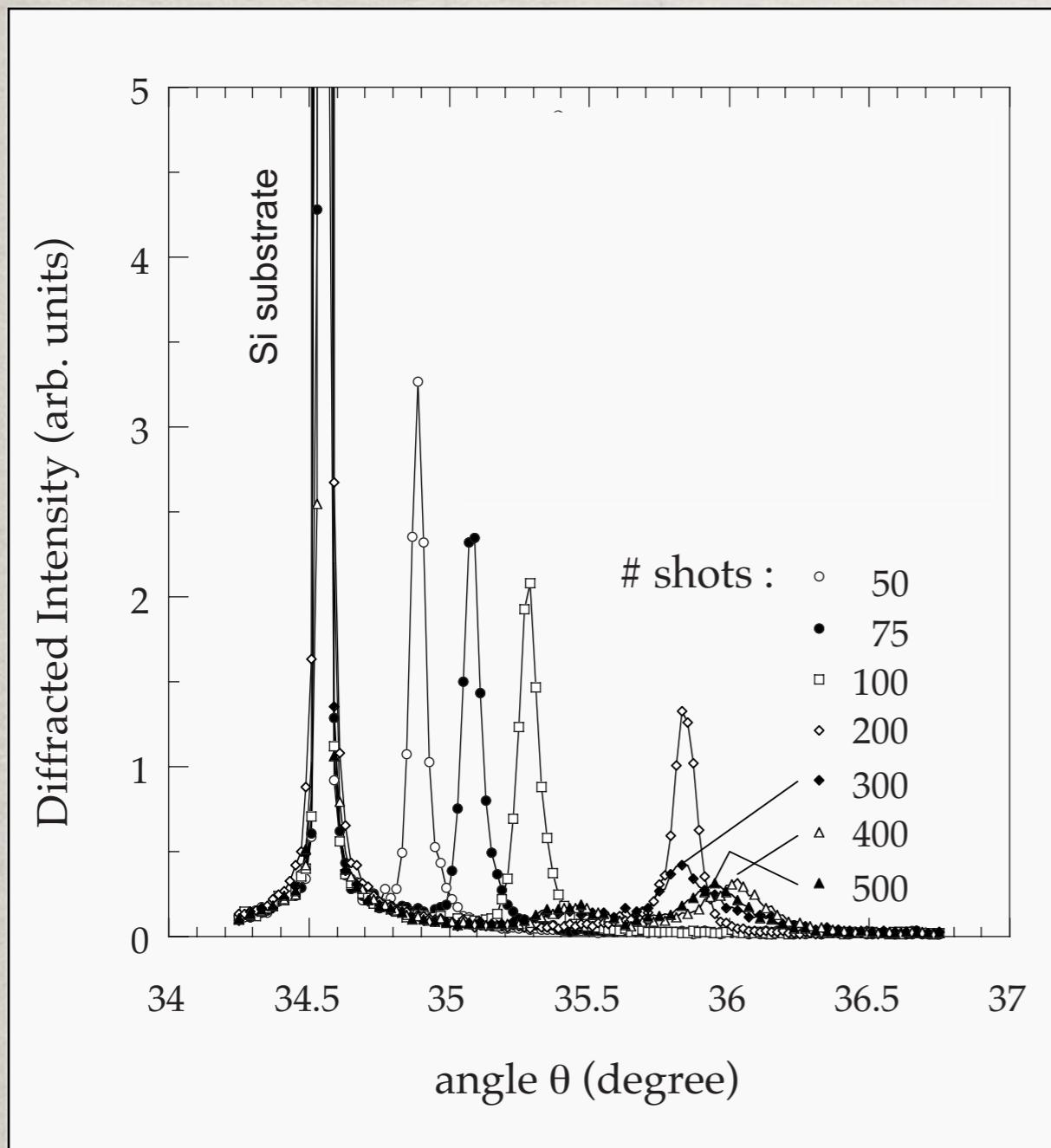
30 nm-thick 7.5 at%

35 nm-thick 5 – 9 at%

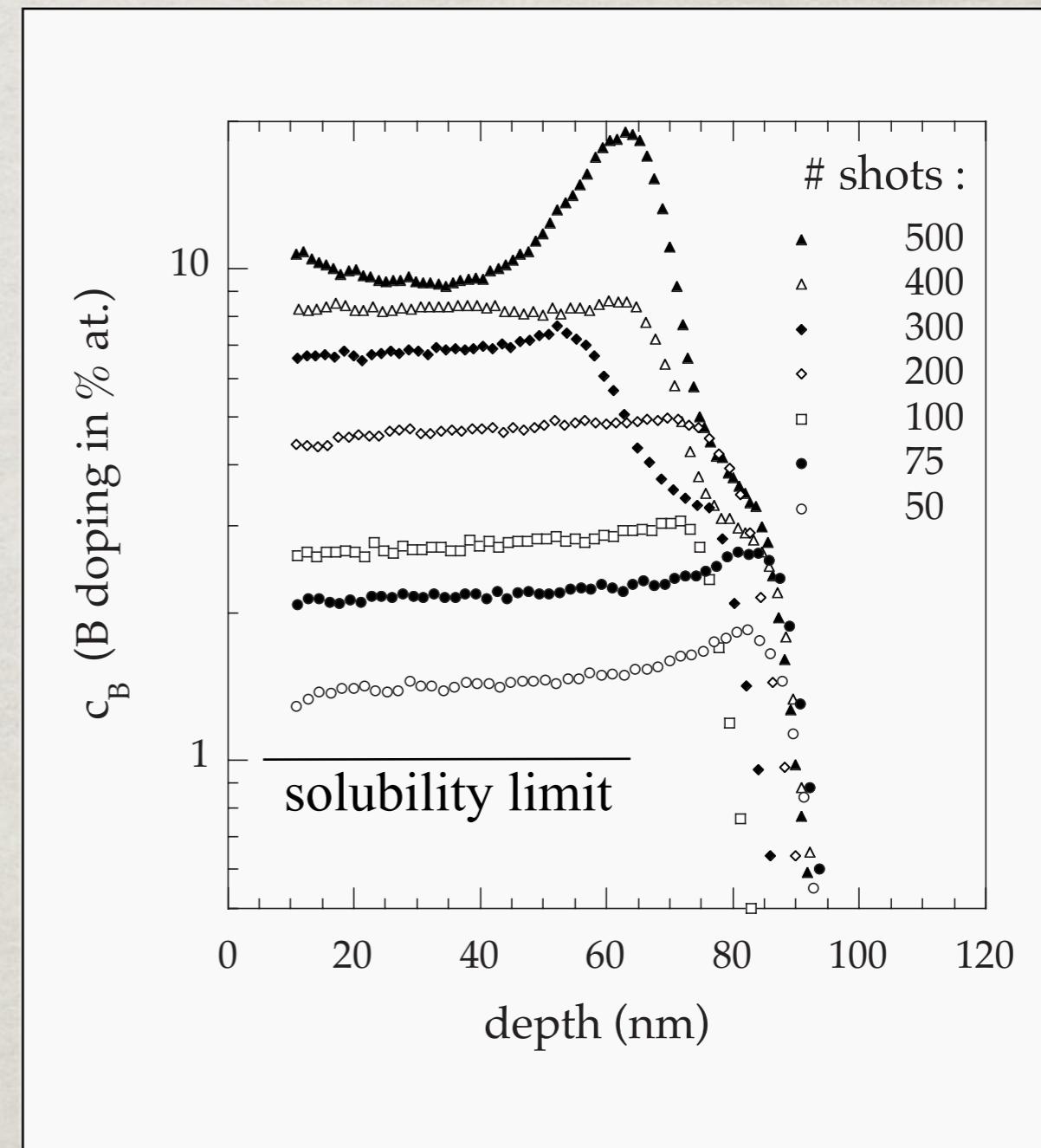
E.Bustarret
C.Marcenat et al. (2004)



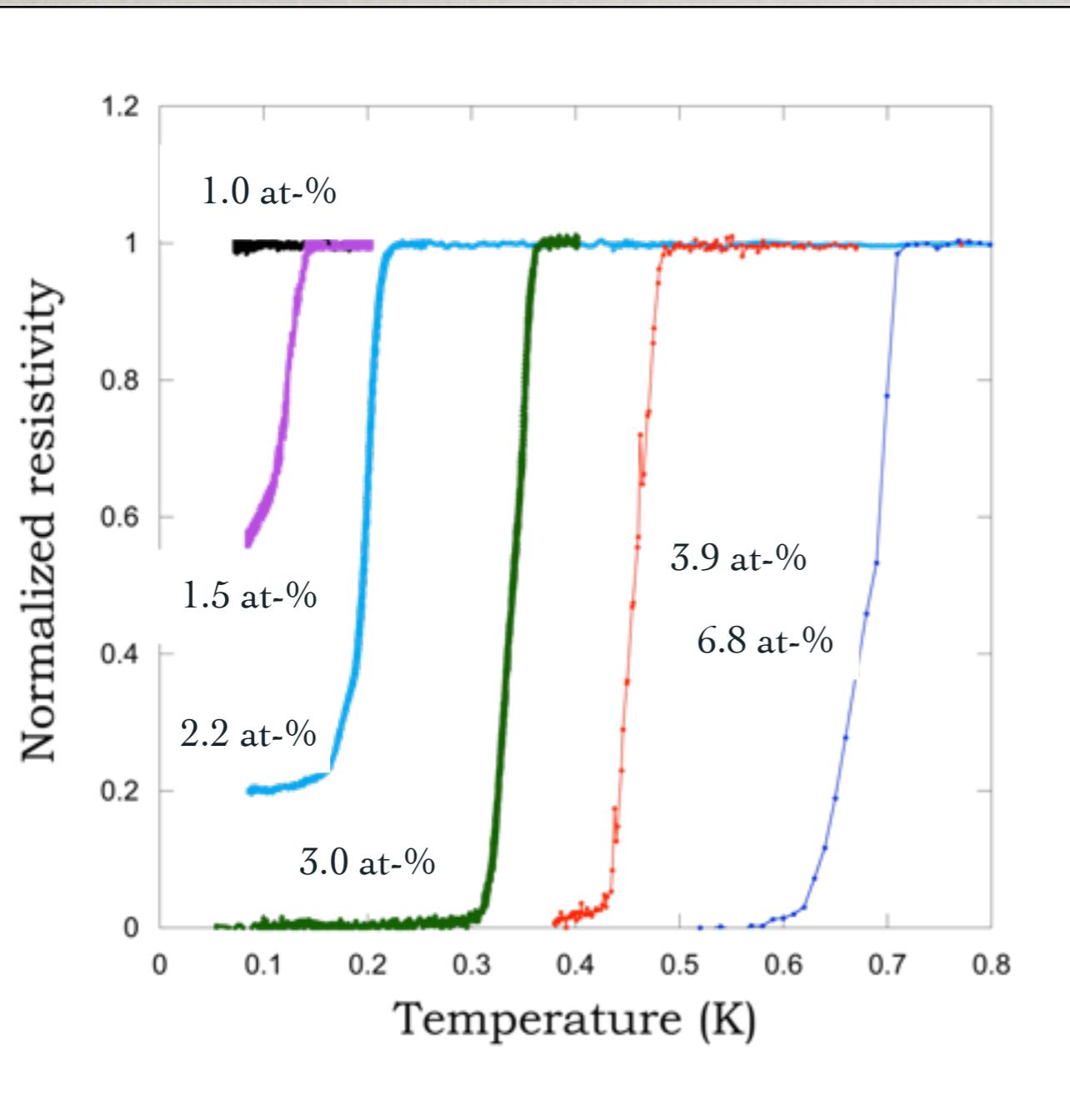
systematic study of $T_c(n_B)$ in a serie of 80nm thin films



X-rays : well defined (shifted) [004] peaks up to 200 shots



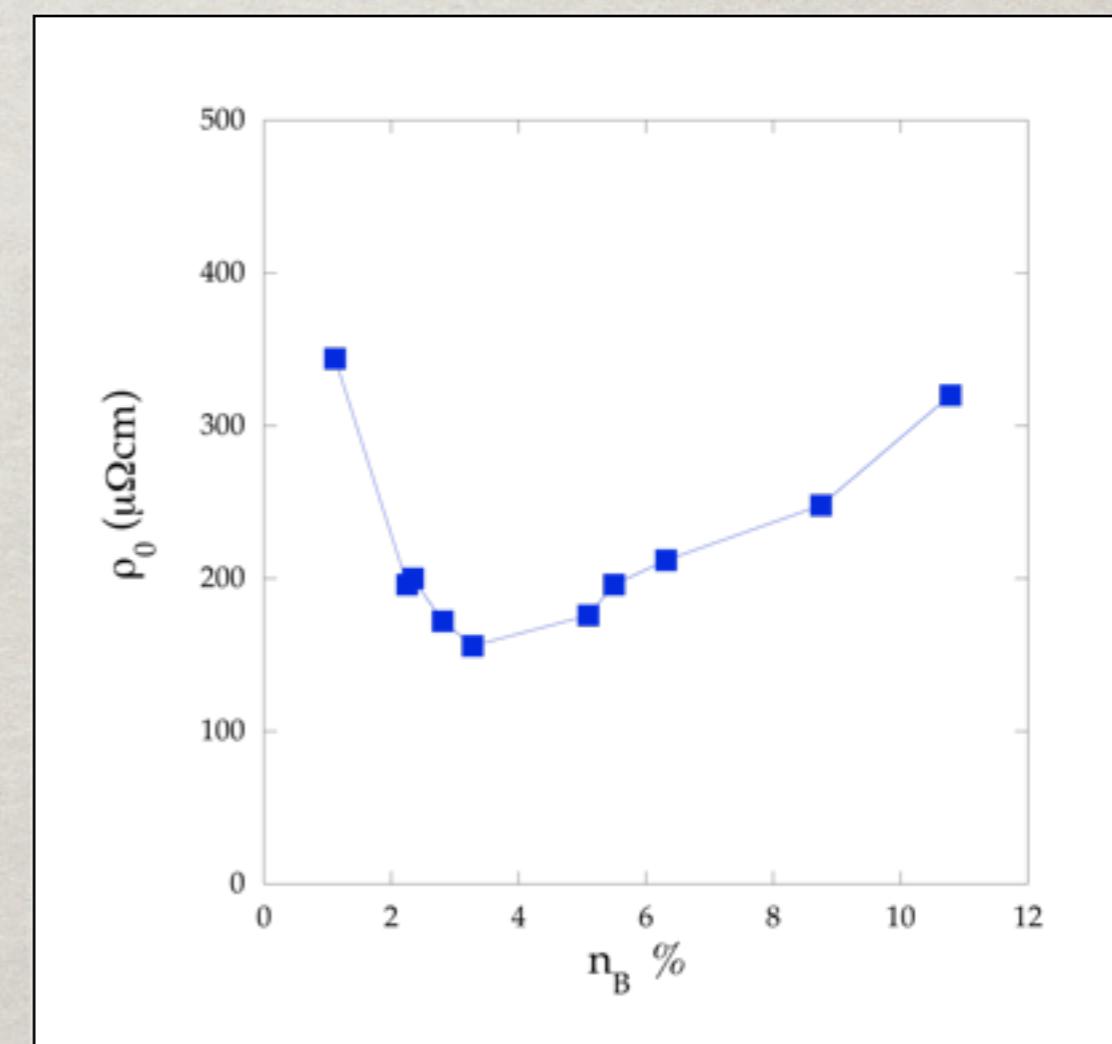
SIMS : homogenous doping level up to 200 shots = 4.5 at% $\sim 2.2 \times 10^{21} \text{ cm}^{-3}$

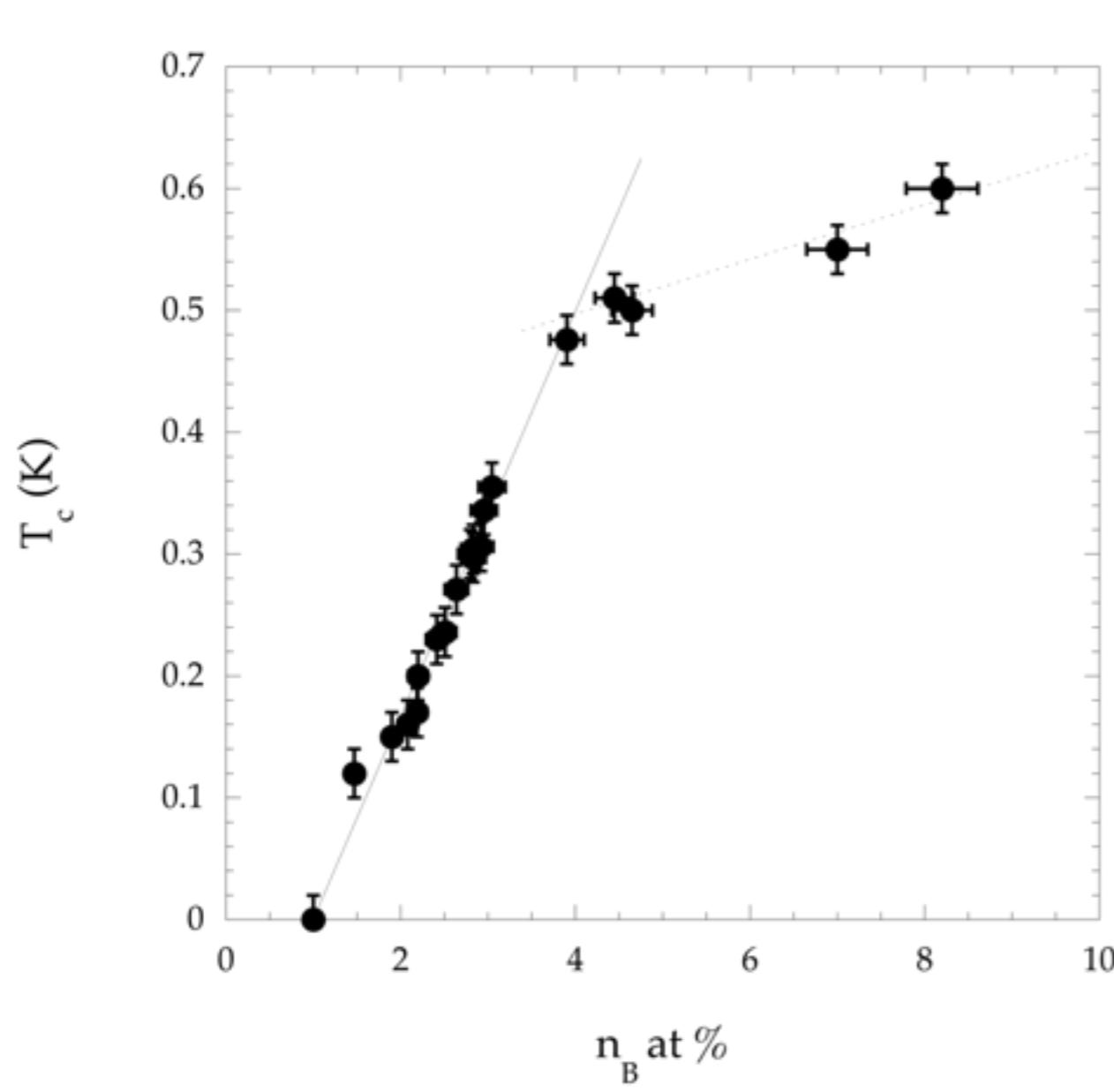


T_c shifted up 0.7K

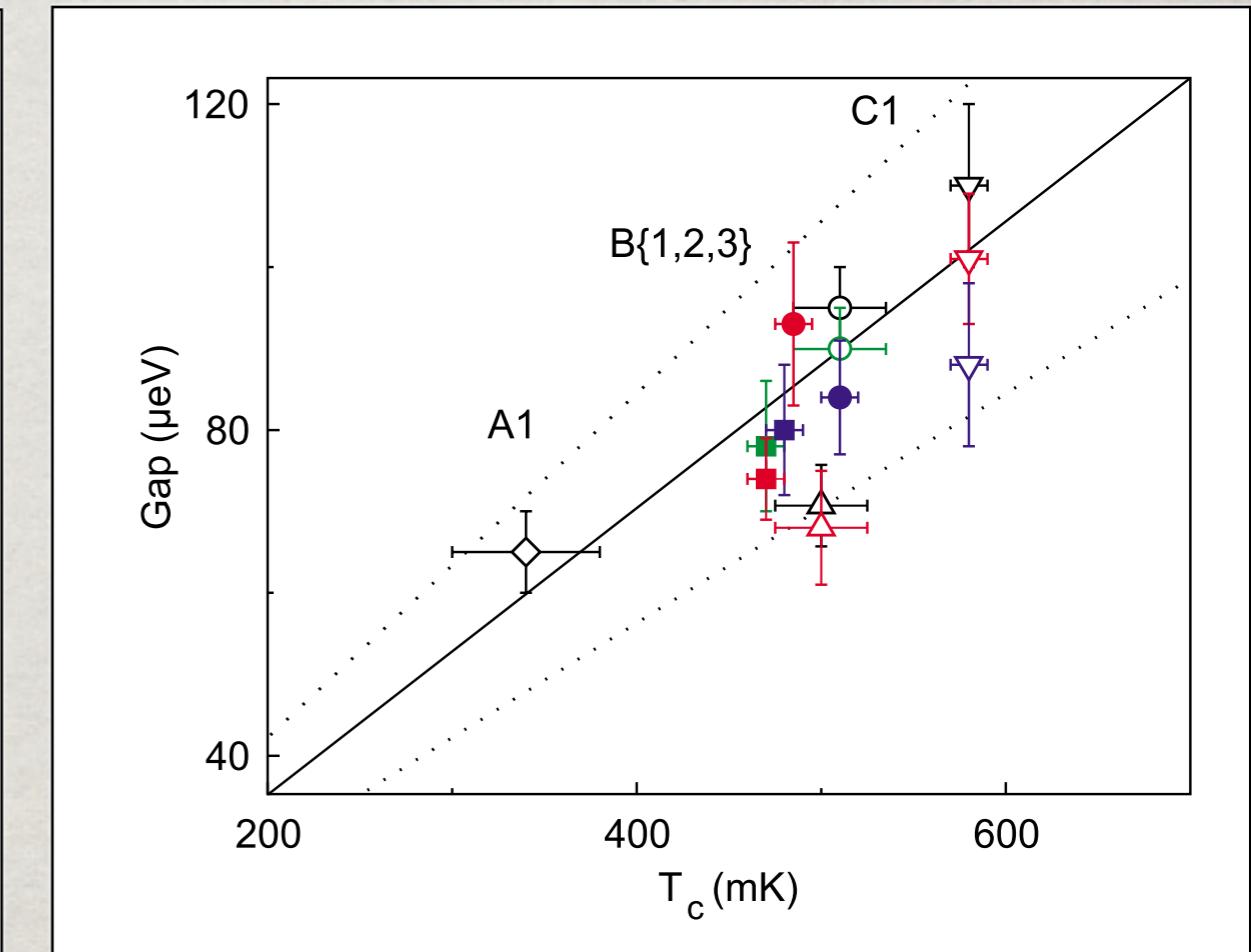
(incomplete transition below ~ 2.5 at-%)

BAD METAL
 $\rho_0 \sim 200 \mu\Omega\text{cm}$
 $R(300\text{K})/R(4\text{K}) \sim 1.2$
 (very flat below 40K)



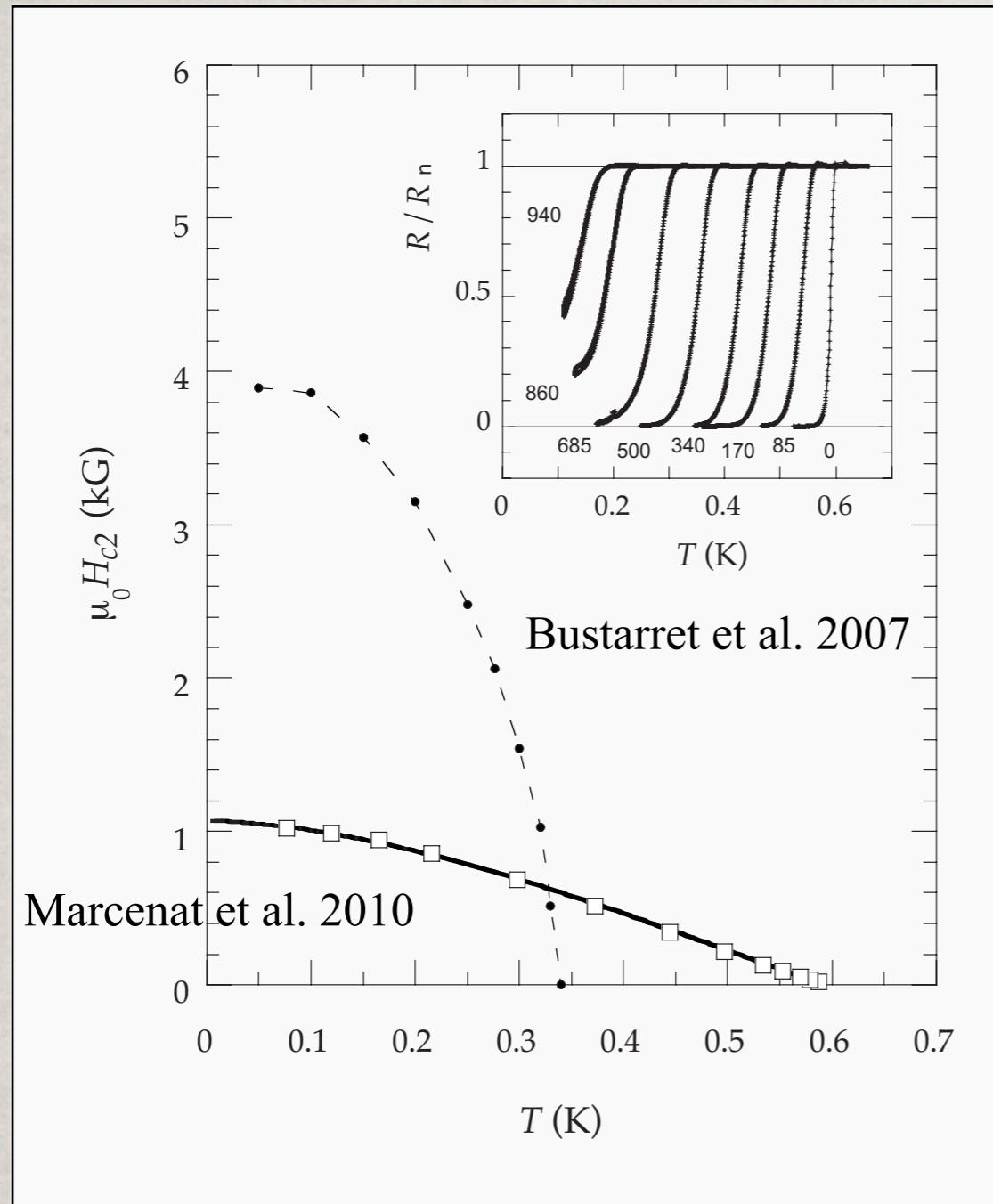


T_c defined at $R/R_n = 0.9$



F.Dahlem et al. (2011)

$\Delta/kT_c \sim 1.7$ i.e. close to BCS value



$H_{c2}(0)$ decreases from 4000G to 1000G in *better* samples

probably type II superconductor
eventhough...

$$\xi = \hbar v_F / \pi \Delta \sim 1000 \text{ nm}$$

$$\lambda = \sqrt{m^* / \mu_0 e^2 n} \sim 60 \text{ nm}$$

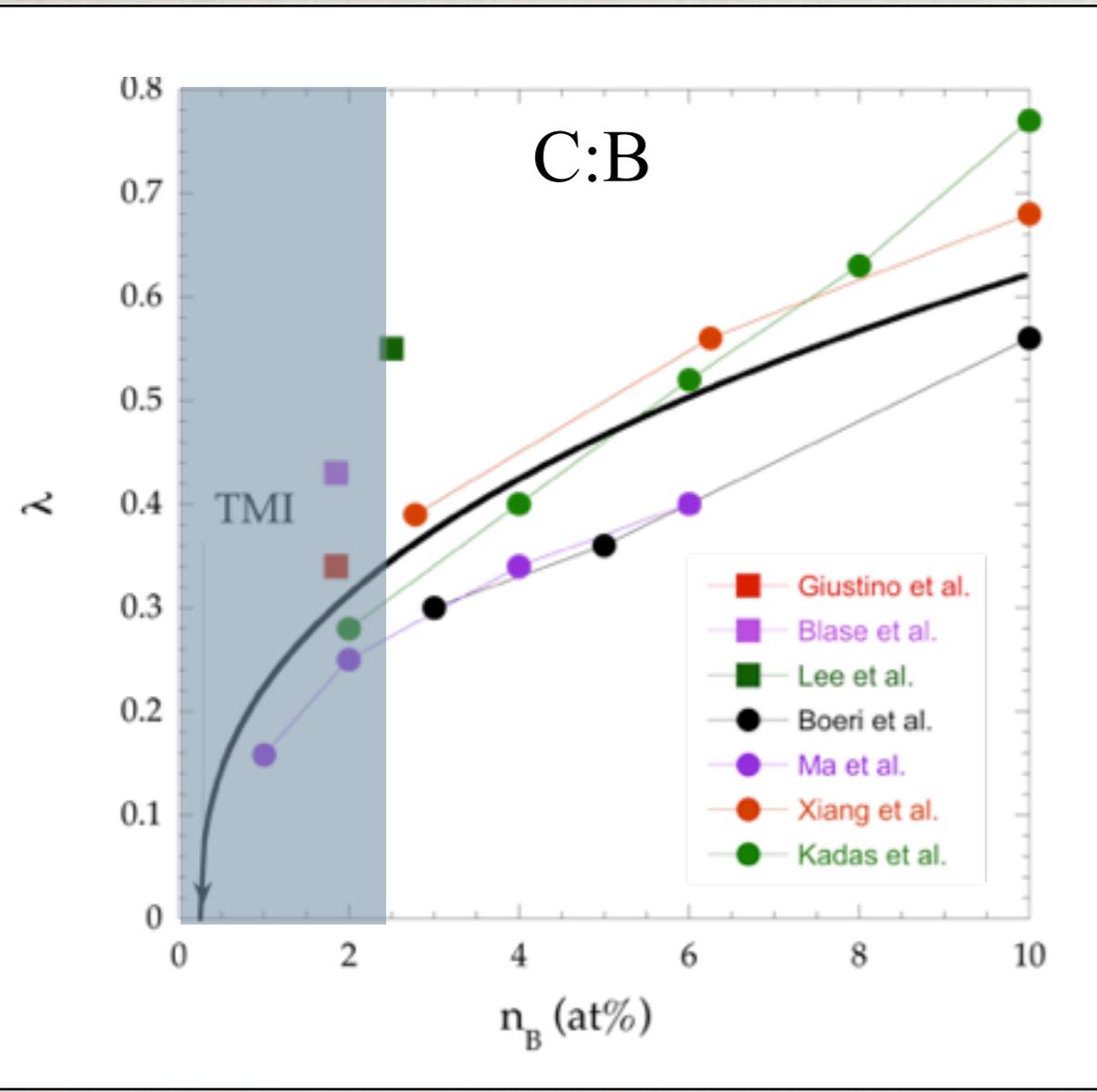
$$\lambda / \xi \ll 1$$

type I superconductivity
observed in SiC (Kriener et al. 2008)

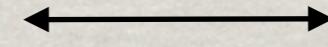
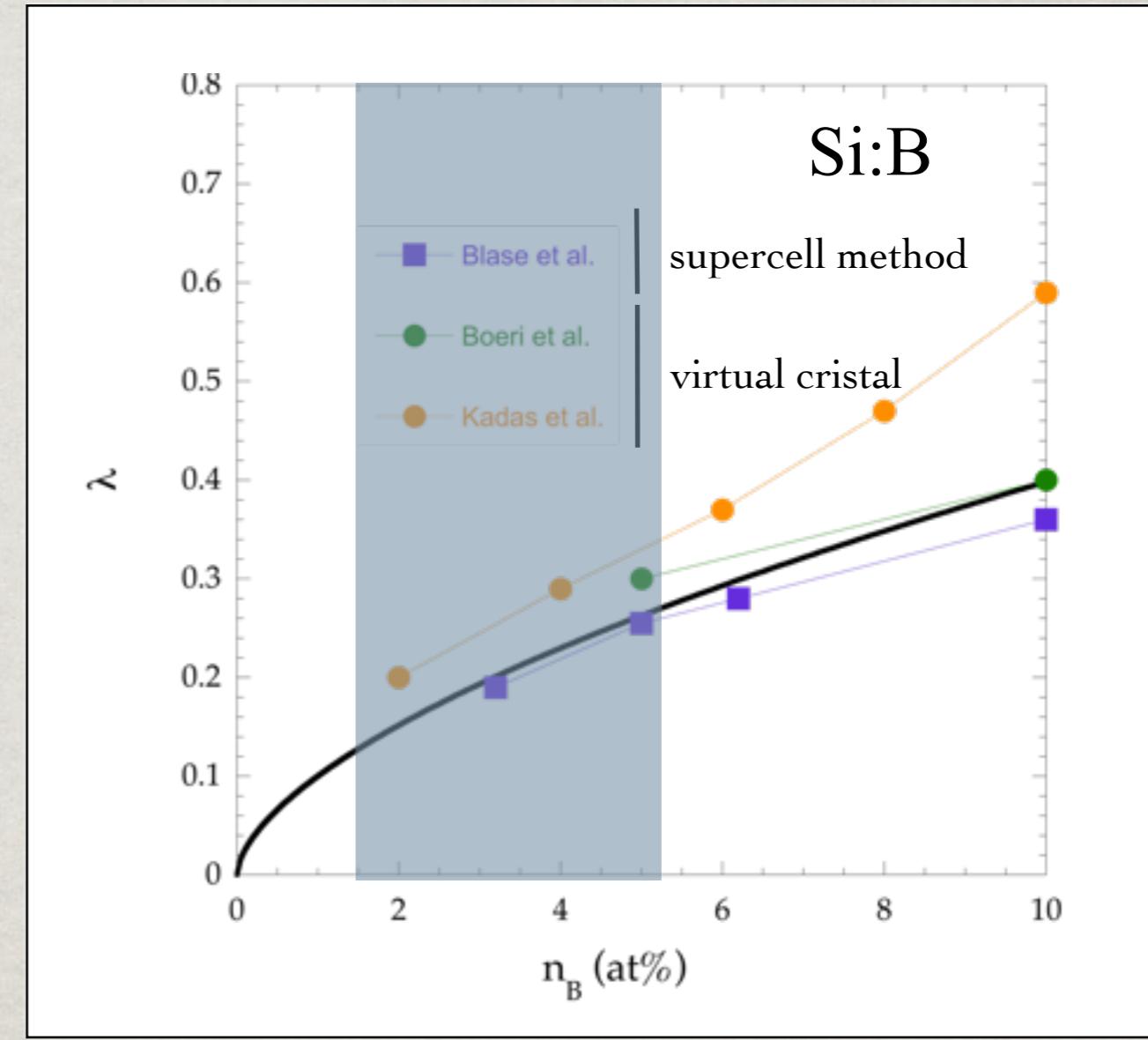
but...

$l \sim 3 \text{ nm} \ll \xi$
DIRTY superconductor

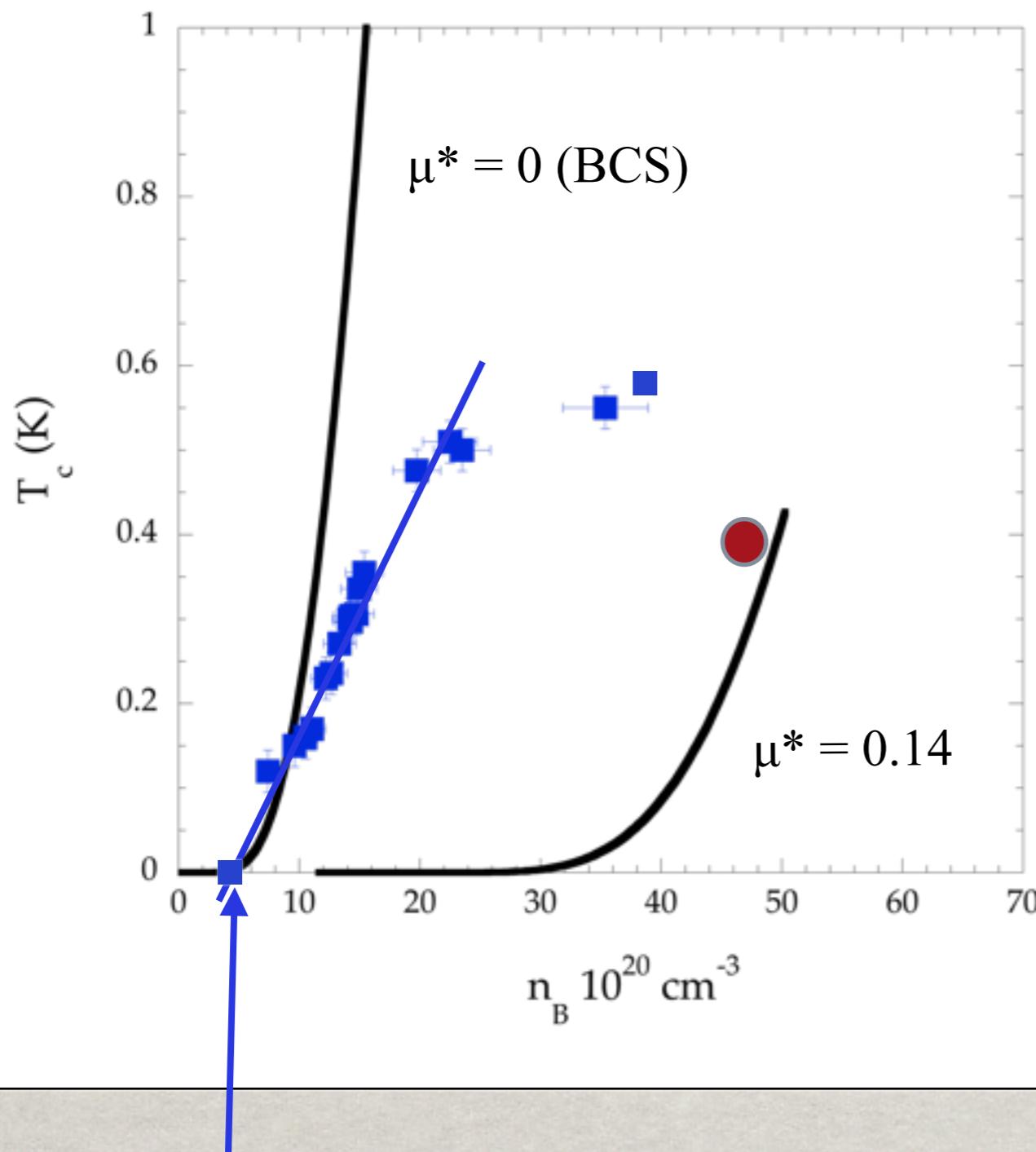
$$\kappa \rightarrow 0.7\lambda/l \gg 1$$



experimental range
for T_c measurements



experimental range
for T_c measurements

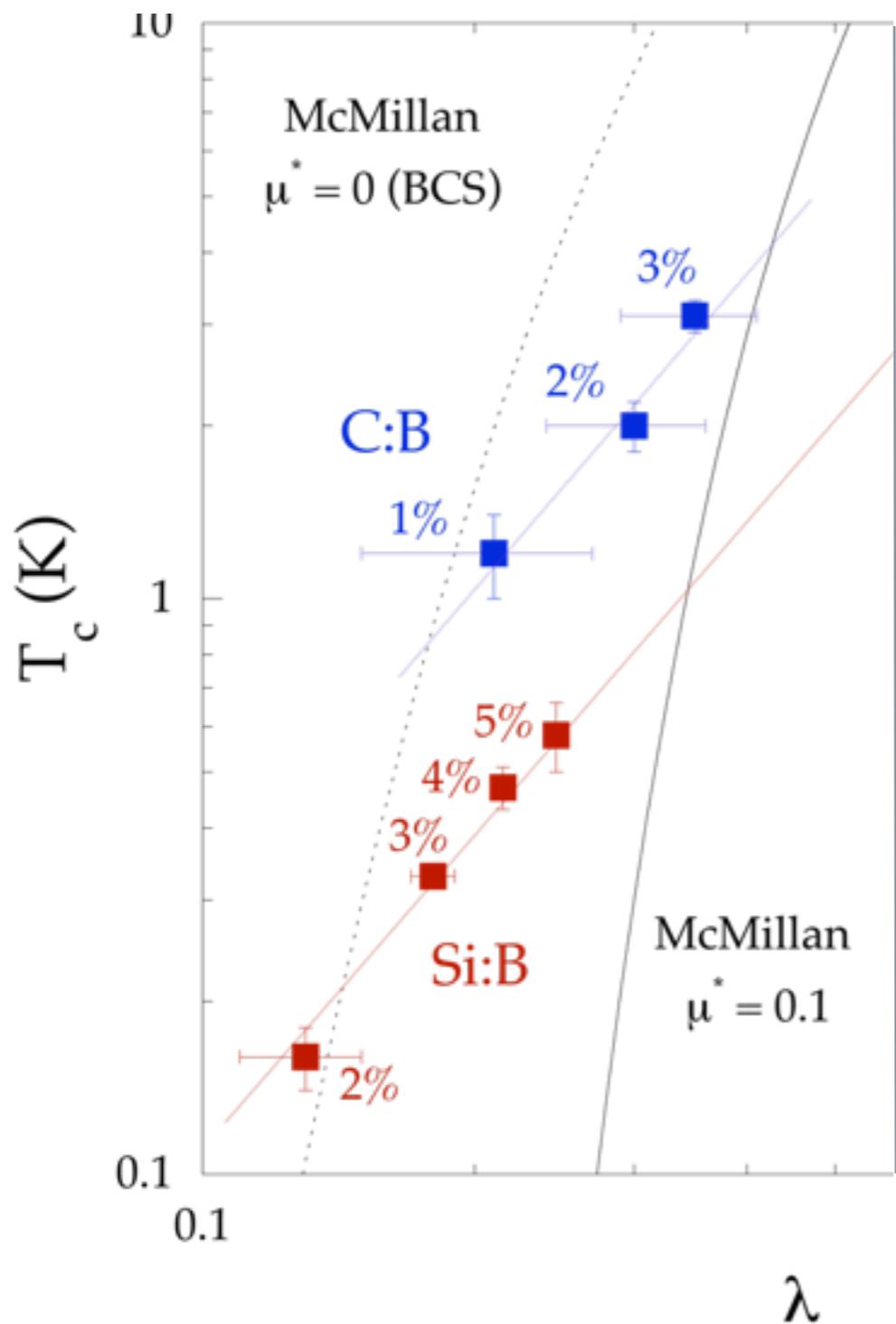


$n^* ?$: **NOT** related to MIT : $n_c \sim 10^{18} \text{ cm}^{-3}$

very reasonable agreement
between calculations and
 T_c obtained by Bustarret et al. (2007)
taking $\mu^* \sim 0.14$
standard metal value

but new data (lower n_B values) led to T_c
AGAIN much larger
than calculated values

can **NOT** be associated with reduced μ^*
 $n_B \gg n_c$



T_c scales
as λ^α
with $\alpha \sim 2$ (0.2)

Has this something to do with
fractality ?

Feigelman et al. (2007)
Disordered system
close to SIT

$$T_c = E_0 \lambda^{1/\gamma} C(\gamma)$$

$$\gamma = 1 - D/3$$

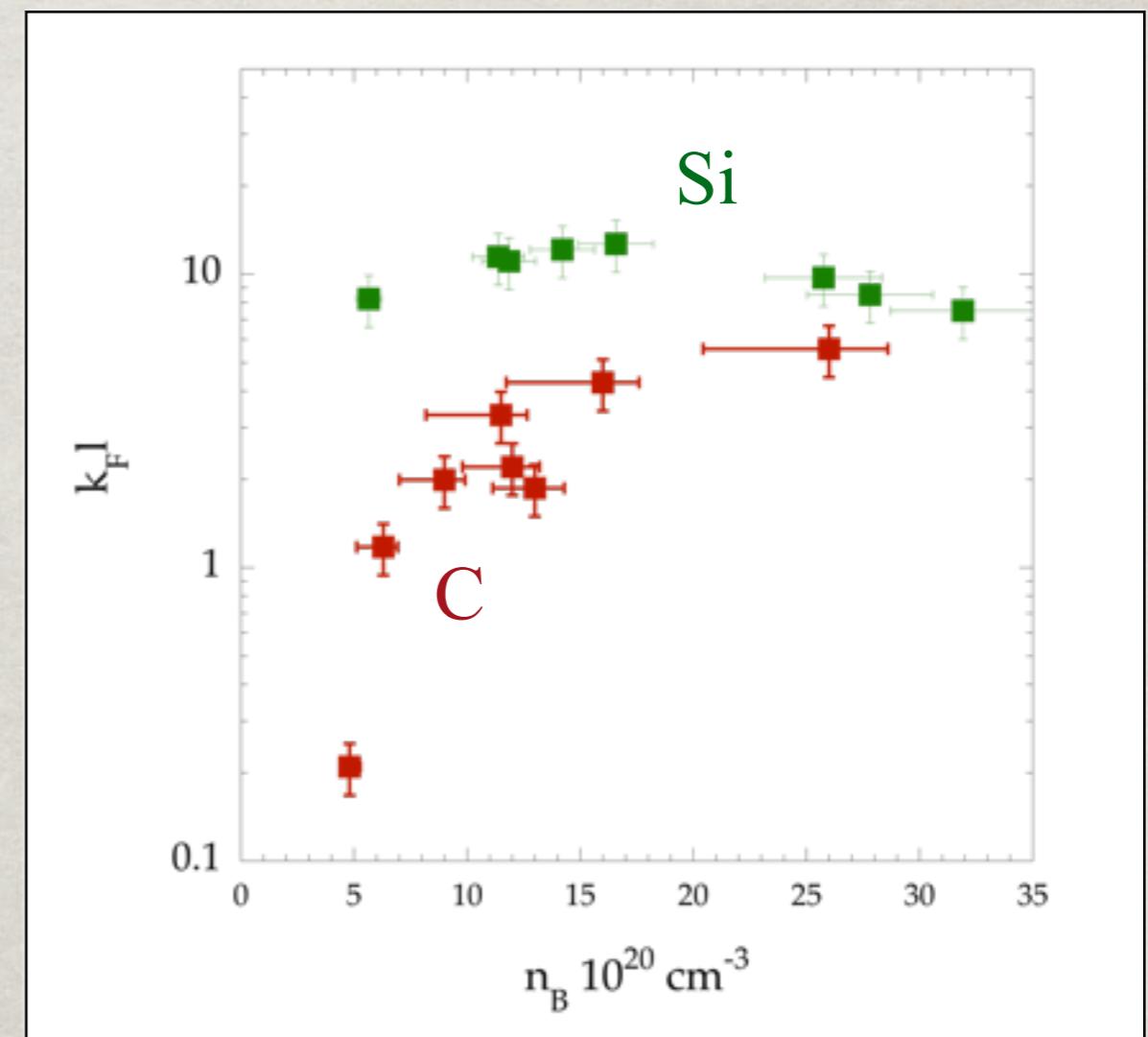
where D is the fractal
dimension of eigenstates

numerical calculation
 $D \sim 1.3$
and $1/\gamma \sim 1.8$

but...

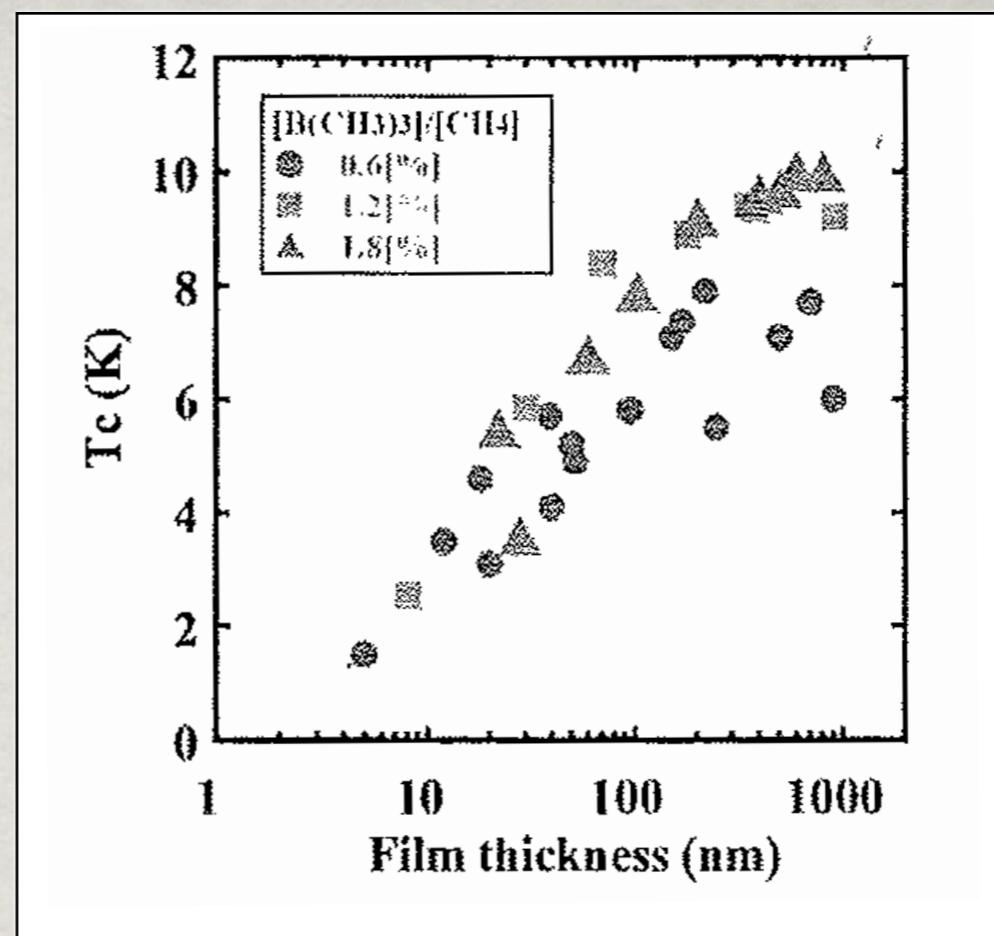
[A] λ calculations made without any disorder nor any strain
(induced in the films by substrate)

[B] if k_{FL} close to 1-3 in C:B
 $k_{\text{FL}} \sim 10$ in Si:B



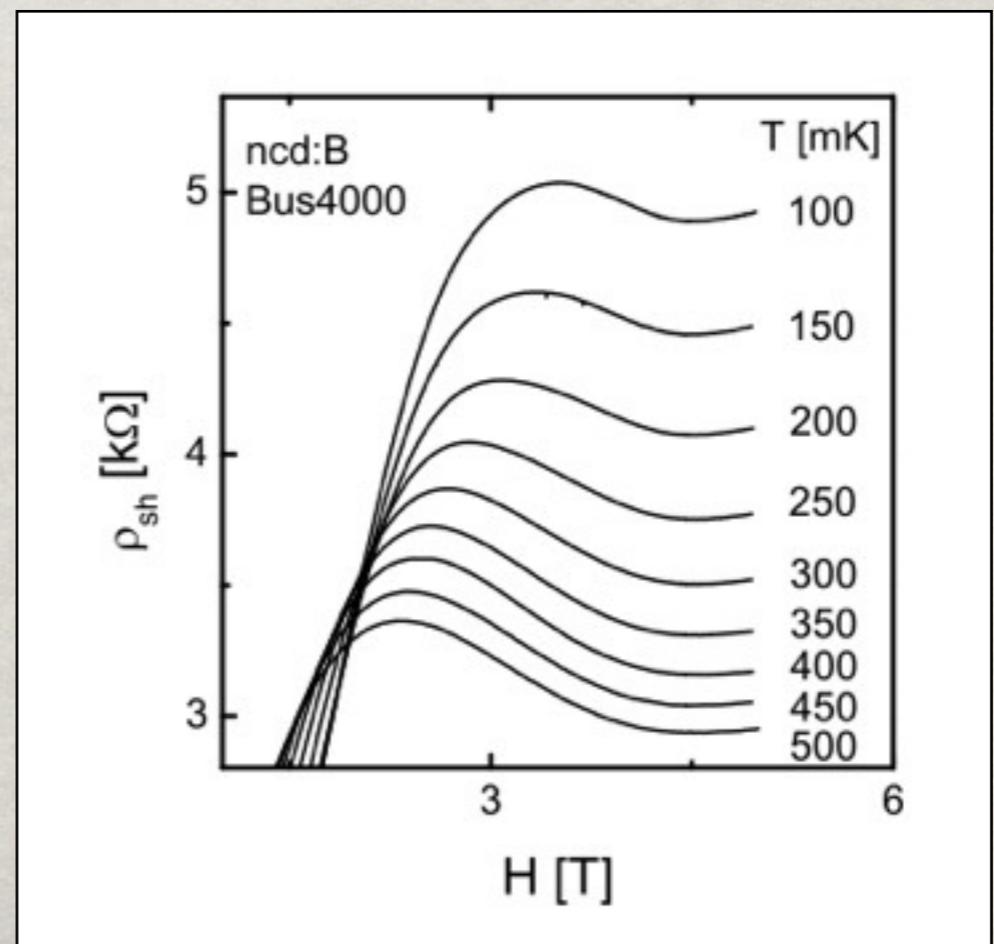
[C] T_c decreases with the film thickness in C:B

Kawarada et al. 2011



[D] small MR peak ($T_c = 1$ K sample B:C nanocrystallites) but no real «crossing point»

P.Achatz et al. 2008



in Conclusion

- (type II) superconductivity obtained in B doped diamond and silicon films
- T_c remains quite large down to the MIT in C:B
$$[T_c \sim (n_B/n_c - 1)^{0.5}]$$
- T_c much larger then expected values deduced from *ab initio* λ calculations in Si:B ($n_B \gg n_c$)
- possible λ^2 scaling of T_c in both Si:B and C:B

Thank you for your attention...